

# Topologické izolátory

ÚFKL

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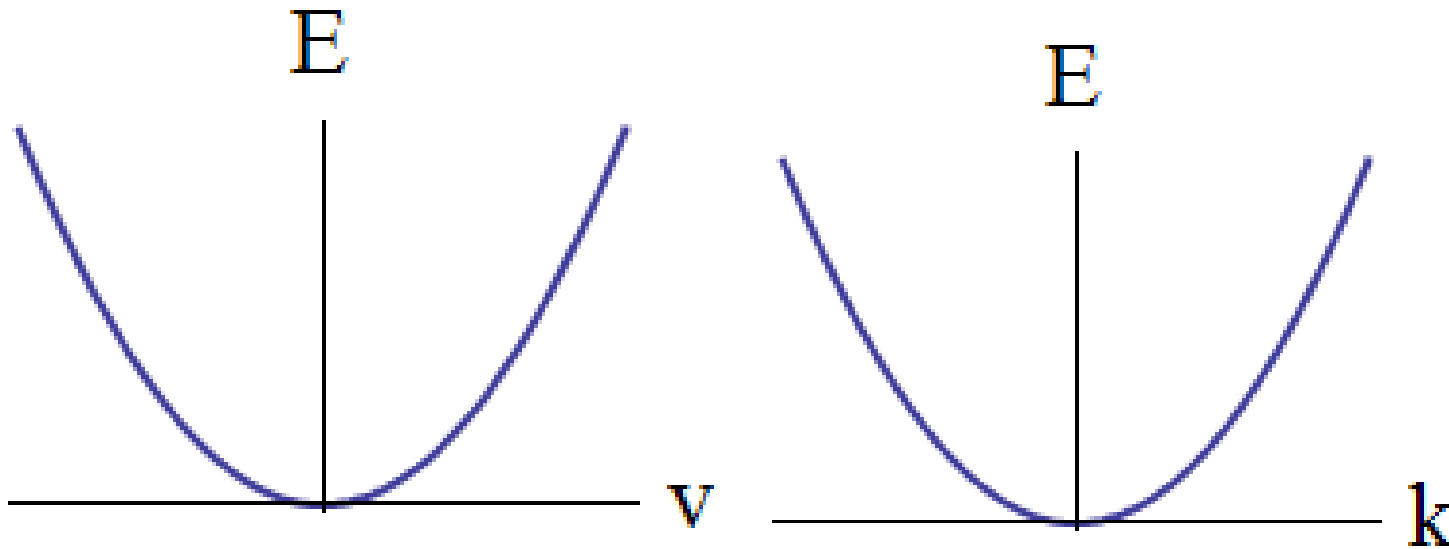
J. Minár, S. Khan - ZČU Plzeň

H. Ebert - Uni Mnichov

# Osnova

- Krátké a stručné přiblížení pásového modelu pevných látek
- Metody měření pásové struktury
- Topologické izolátory
- Některé experimentální výsledky

# Pásová struktura



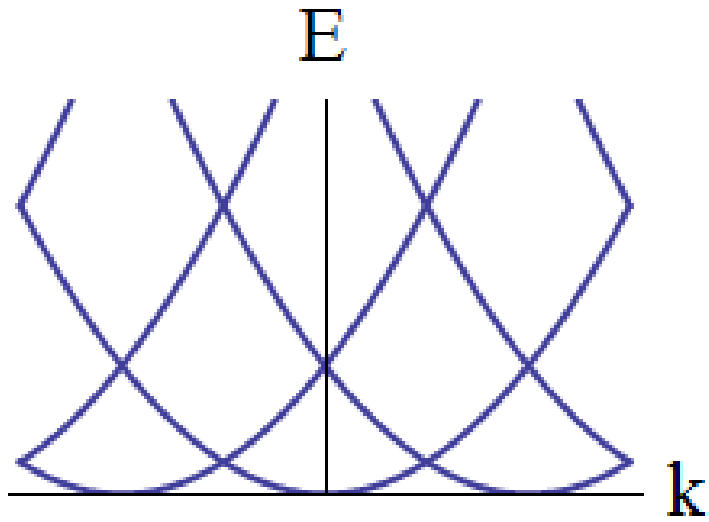
Závislost kinetické energie elektronu na rychlosti

$$E = mv^2/2$$

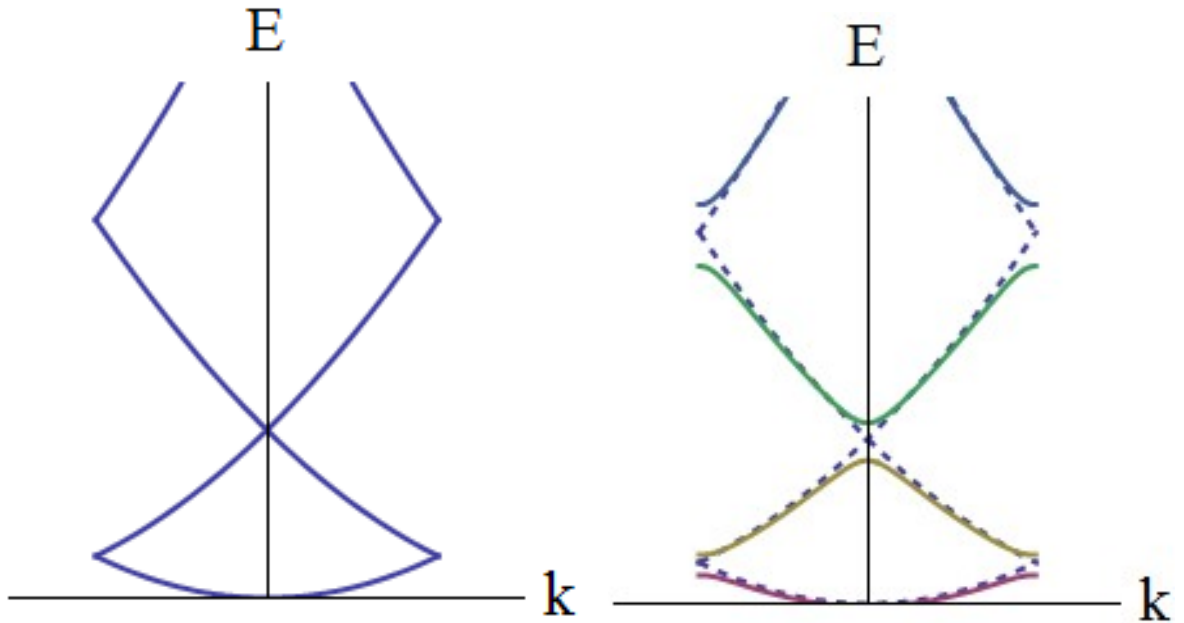
hybnost  $p = mv$   $E = p^2/2m$

vlnový vektor  $p = \hbar k$   $E = \hbar^2 k^2 / 2m$

# Pásová struktura

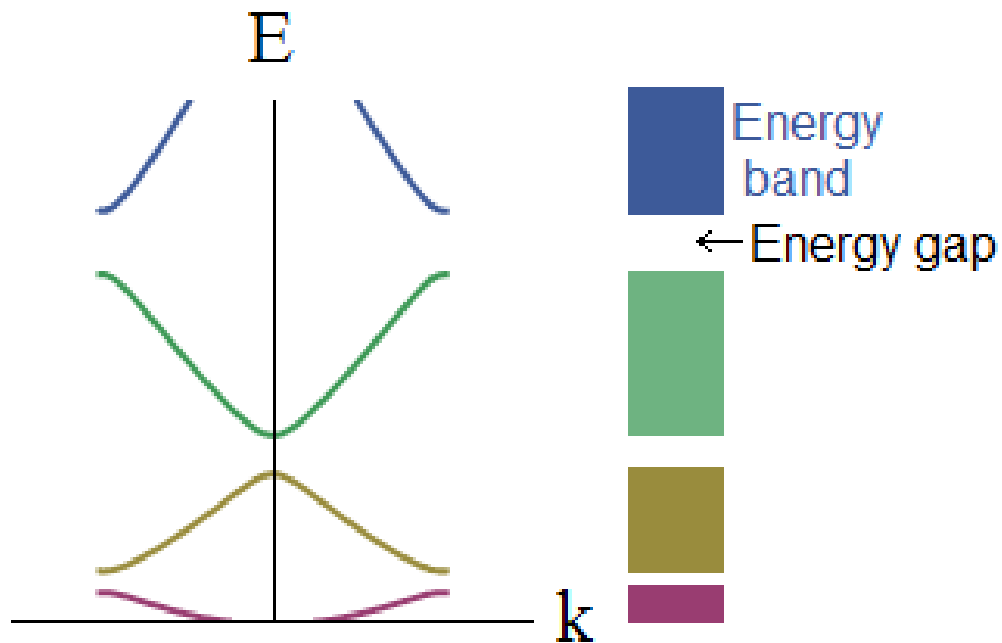


Elektron v krystalové mříži



Vliv elektrostatické interakce s jádry atomů i elektrony navzájem

# Pásová struktura



Pásová struktura

Pauliho vylučovací princip

Kovy: zcela zaplněný pás  
snadná vedení proudu

Zcela zaplněný pás izolátory a polovodiče.

Polovodiče mají zakázaný pás relativně úzký (do cca 4eV), možnost tepelné excitace elektronů, dopování

# Pásová struktura

Periodic Table of the Elements © www.elementsdatabase.com

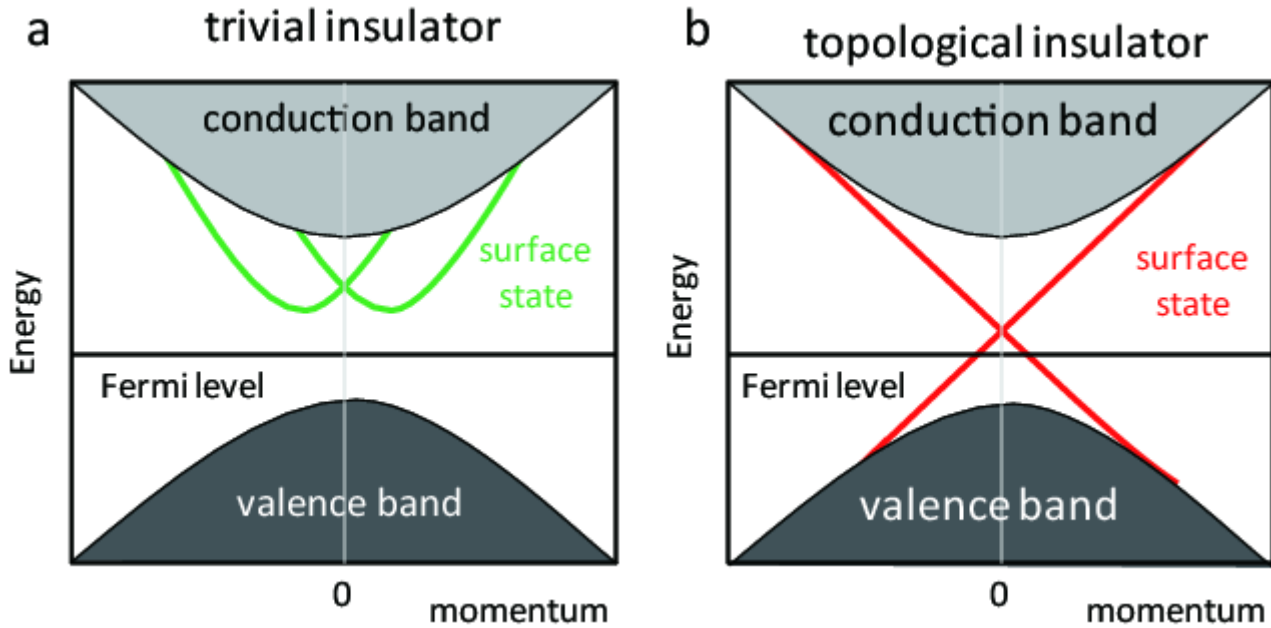
1 H																	2 He
3 Li	4 Be											5 B	6 C	7 N	8 O	9 F	10 Ne
11 Na	12 Mg											13 Al	14 Si	15 P	16 S	17 Cl	18 Ar
19 K	20 Ca	21 Sc	22 Ti	23 V	24 Cr	25 Mn	26 Fe	27 Co	28 Ni	29 Cu	30 Zn	31 Ga	32 Ge	33 As	34 Se	35 Br	36 Kr
37 Rb	38 Sr	39 Y	40 Zr	41 Nb	42 Mo	43 Tc	44 Ru	45 Rh	46 Pd	47 Ag	48 Cd	49 In	50 Sn	51 Sb	52 Te	53 I	54 Xe
55 Cs	56 Ba	57 La	72 Hf	73 Ta	74 W	75 Re	76 Os	77 Ir	78 Pt	79 Au	80 Hg	81 Tl	82 Pb	83 Bi	84 Po	85 At	86 Rn
87 Fr	88 Ra	89 Ac	104 Unq	105 Unp	106 Unh	107 Uns	108 Uno	109 Une	110 Unn								

58 Ce	59 Pr	60 Nd	61 Pm	62 Sm	63 Eu	64 Gd	65 Tb	66 Dy	67 Ho	68 Er	69 Tm	70 Yb	71 Lu
90 Th	91 Pa	92 U	93 Np	94 Pu	95 Am	96 Cm	97 Bk	98 Cf	99 Es	100 Fm	101 Md	102 No	103 Lr

# Topologické izolátory

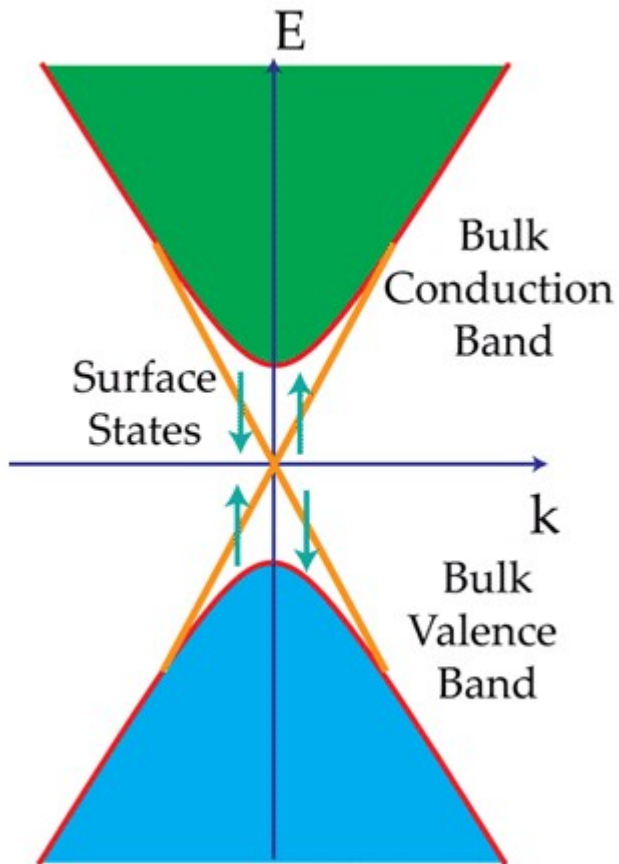
## Pásová struktura topologického izolátoru

Povrchové stavy polarizovaného spinu



# Topologické izolátory

## Pásová struktura topologického izolátoru



Povrchové stavy polarizovaného spinu



# Topologické izolátory

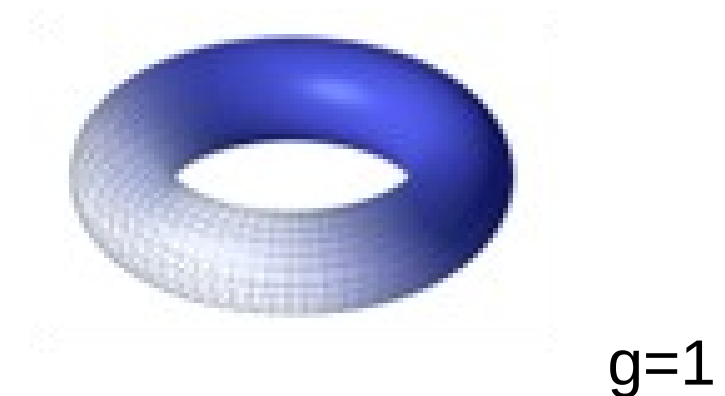
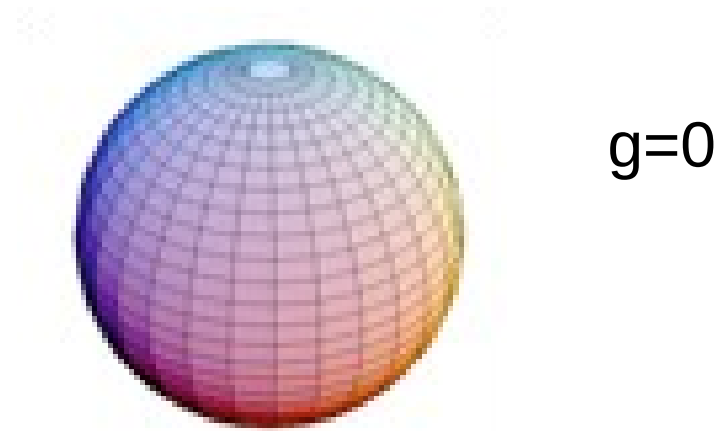
Topologie

Gaussův-Bonnetův teorém

$$\kappa = (r_1 r_2)^{-1}$$

$$\int_M \kappa dA = 2\pi\chi = 2\pi(2 - 2g)$$

$g$  je genus - "počet děr"



# Topologické izolátory

V pásové struktuře

$$\psi(\mathbf{r}) = e^{i\mathbf{k}\cdot\mathbf{r}} u_{\mathbf{k}}(\mathbf{r})$$

$$A = \langle u_{\mathbf{k}} | -i\nabla_{\mathbf{k}} | u_{\mathbf{k}} \rangle$$

$$F = \nabla \times A \quad \text{Berryho křivost}$$

Integrál přes obsazené stavy - Chernovo číslo  $n$

Důsledek:

na rozhraní dvou oblastí s různým Chernovým číslem musí existovat povrchové stavy s jistými vlastnostmi, které nezávisí na stavu povrchu (defekty apod.)

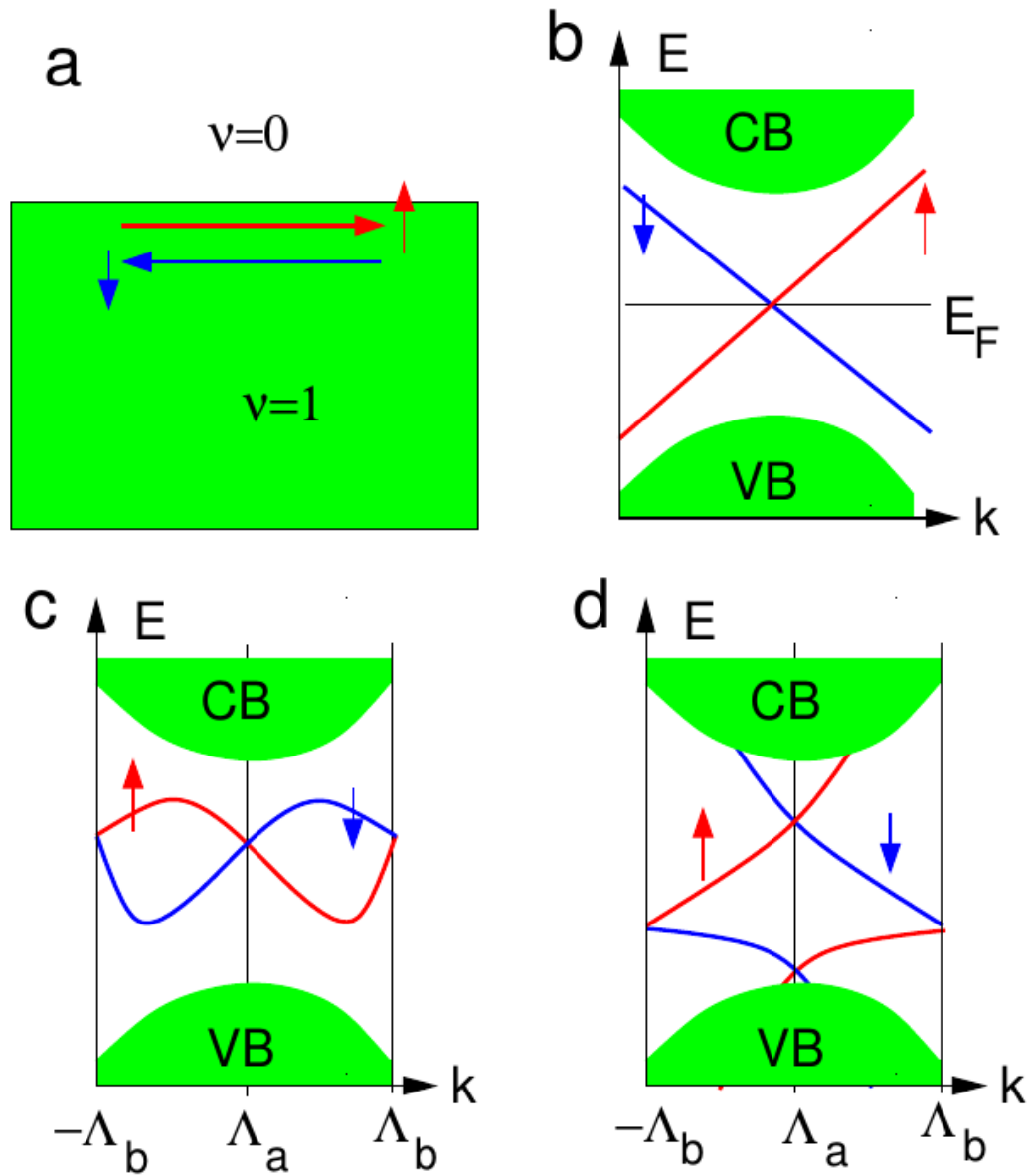
NC 2016: David J. Thouless, Duncan Haldane a Michael Kosterlitz

“za teoretické objevy topologických fází hmoty a topologických fázových přechodů”

Různé invarianty  $Z_0$ ,  $Z_2$ , atd.

Jiná rodina topologických izolátorů (Pb,Sn)Se, (Pb,Sn)Te

# Topologické izolátory



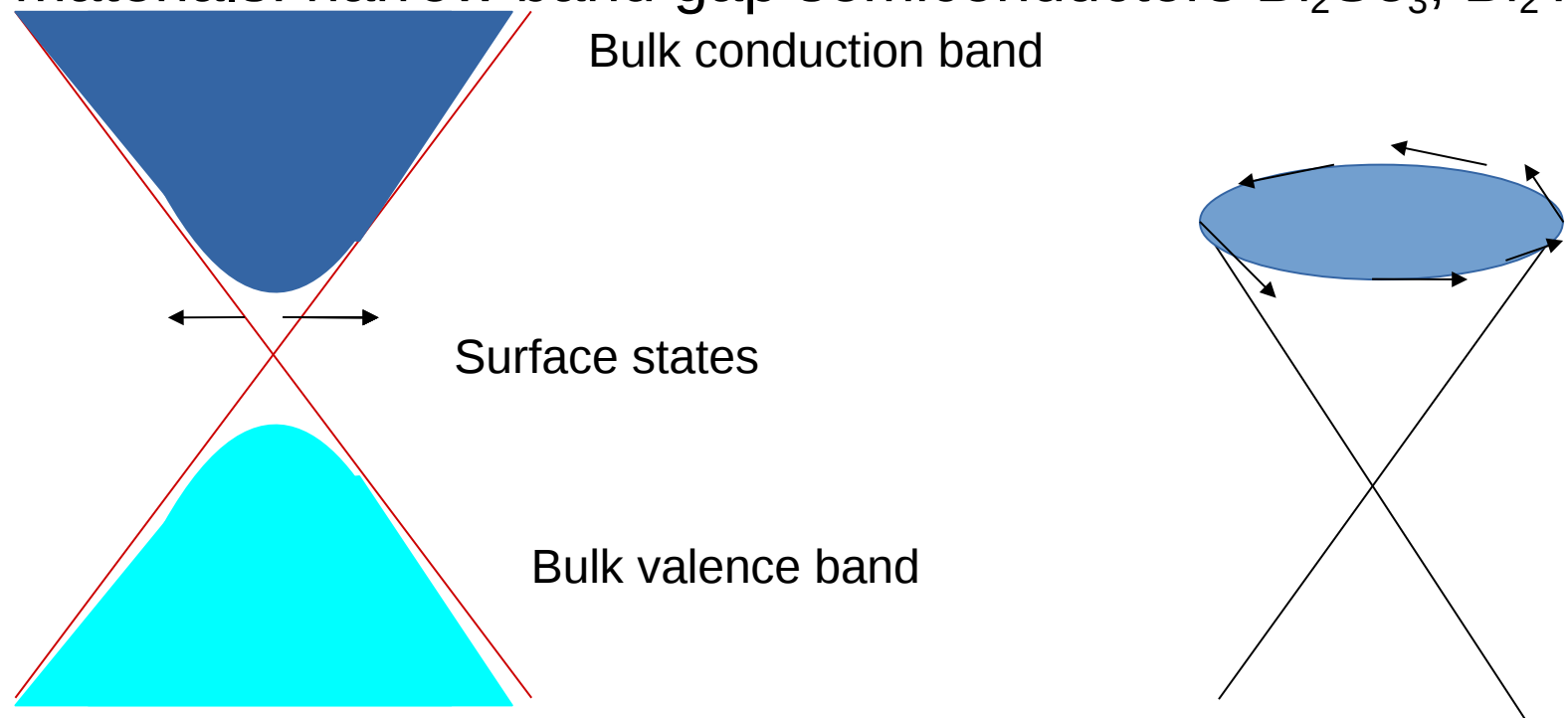
# Topological insulators

Band structure of topological insulator:

Large spin orbit splitting and time reversal symmetry

→ spin polarized surface states with Dirac-cone dispersion

Prototypical materials: narrow band gap semiconductors  $\text{Bi}_2\text{Se}_3$ ,  $\text{Bi}_2\text{Te}_3$

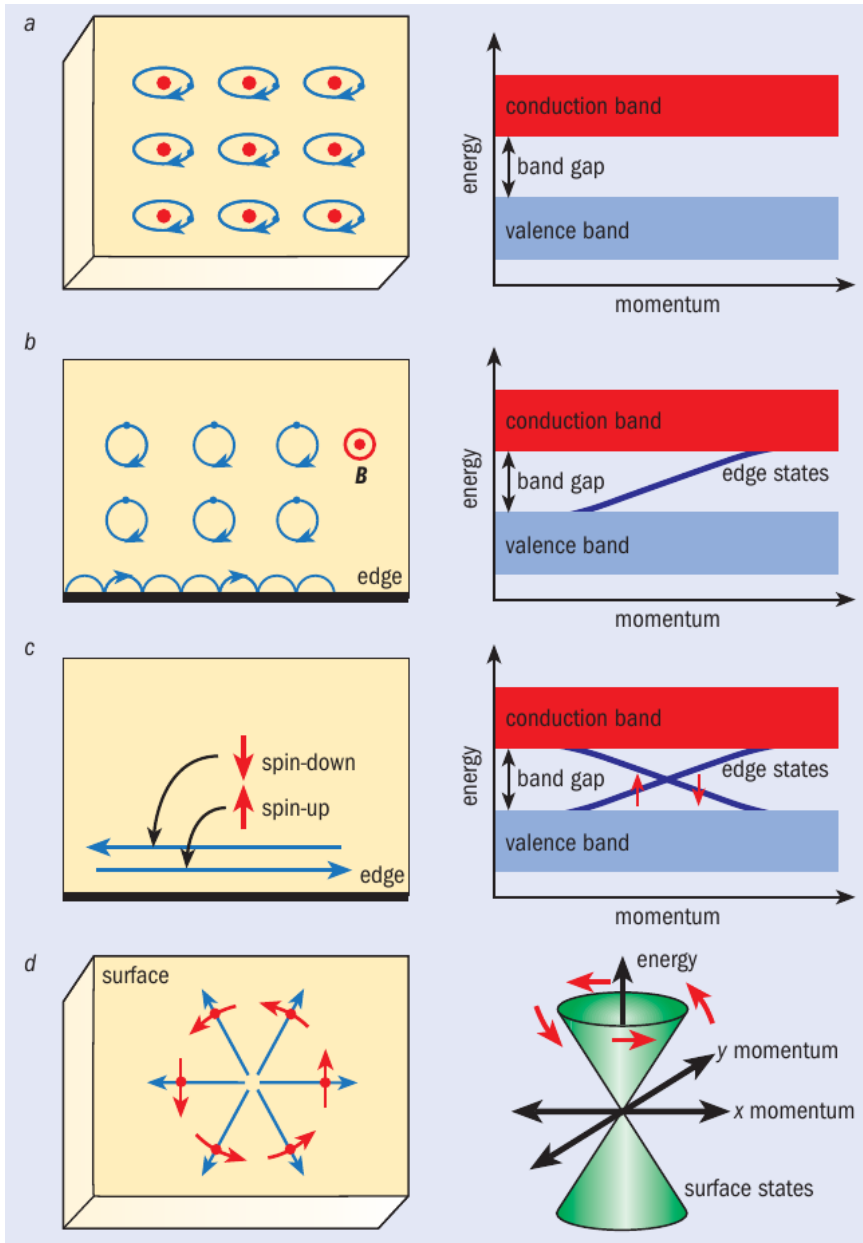


Ferromagnetic ordering brakes time reversal symmetry

→ band gap within surface states, Quantum anomalous Hall effect

# Topologické izolátory

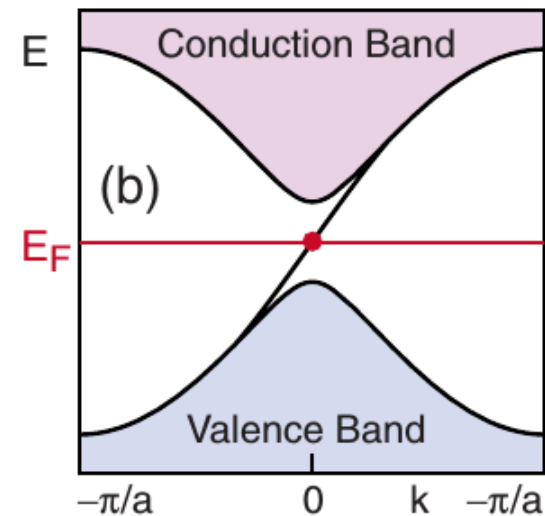
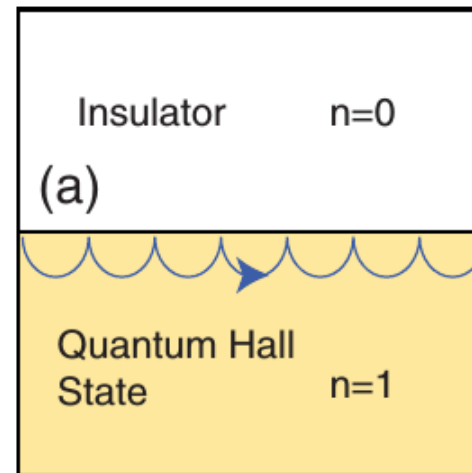
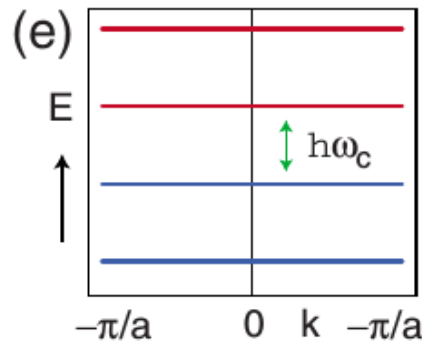
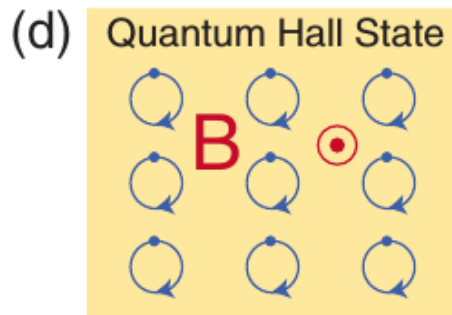
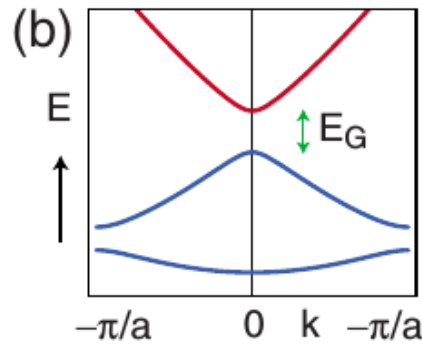
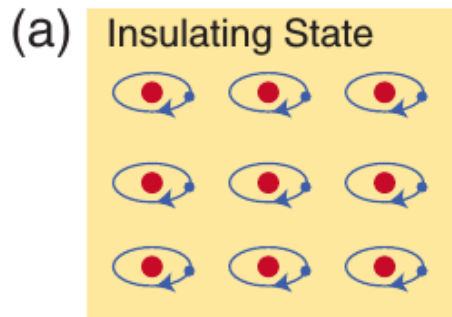
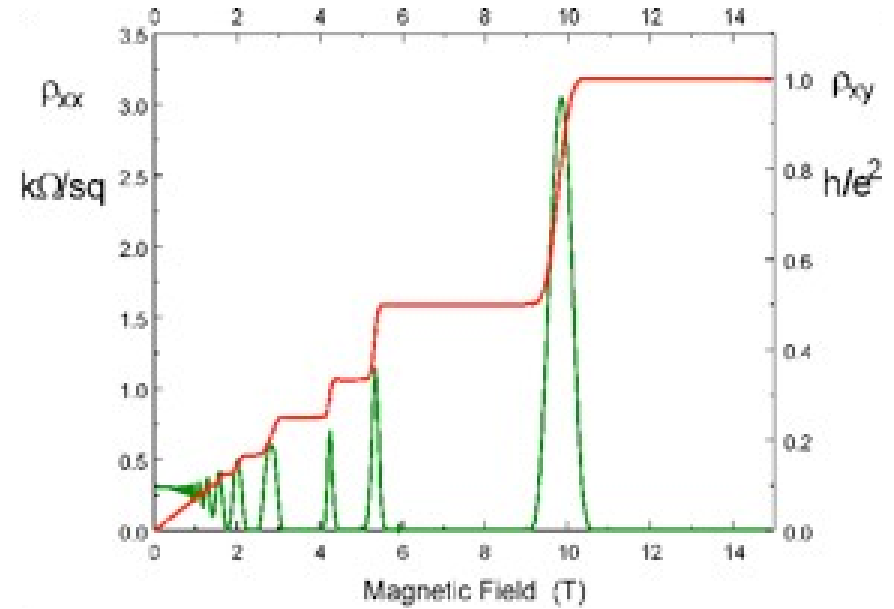
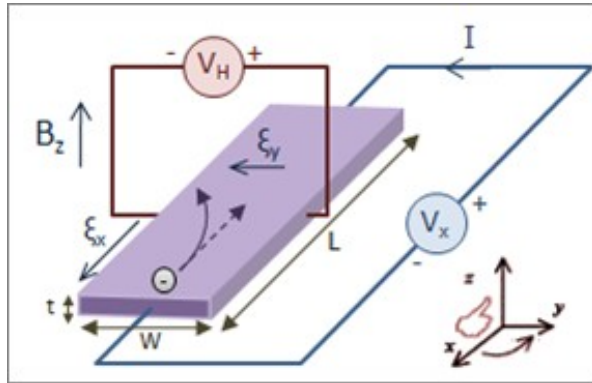
## Pásová struktura topologického izolátoru



(a) The insulating state is characterized by an energy gap separating the occupied and empty electronic states, which is a consequence of the quantization of the energy of atomic orbitals. (b) In the quantum Hall effect, the circular motion of electrons in a magnetic field,  $B$ , is interrupted by the sample boundary. At the edge, electrons execute “skipping orbits” as shown, ultimately leading to perfect conduction in one direction along the edge. (c) The edge of the “quantum spin Hall effect state” or 2D topological insulator contains left-moving and right-moving modes that have opposite spin and are related by time-reversal symmetry. This edge can also be viewed as half of a quantum wire, which would have spin-up and spin-down electrons propagating in both directions. (d) The surface of a 3D topological insulator supports electronic motion in any direction along the surface, but the direction of the electron’s motion uniquely determines its spin direction and vice versa. The 2D energy–momentum relation has a “Dirac cone” structure similar to that in graphene.

# Topologické izolátory

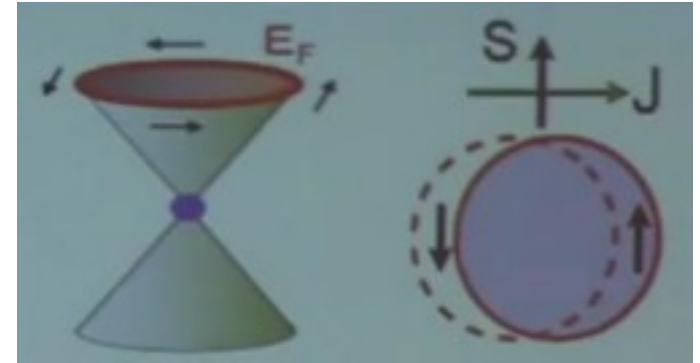
První podobný stav: Kvantový Hallův jev



# Topologické izolátory

Vlastnosti topologických izolátorů:

- proud je úměrný magnetizaci
  - nové aplikační možnosti
- Absence zpětného rozptylu elektronů
  - vysoké pohyblivosti až  $10000\text{cm}^2/\text{Vs}$ , elektronika s malým příkonem
- Robustní vůči nemagnetickým nečistotám
  - povrchové stavy jsou důsledkem symetrie



# Topologické izolátory

Další možné aplikace:

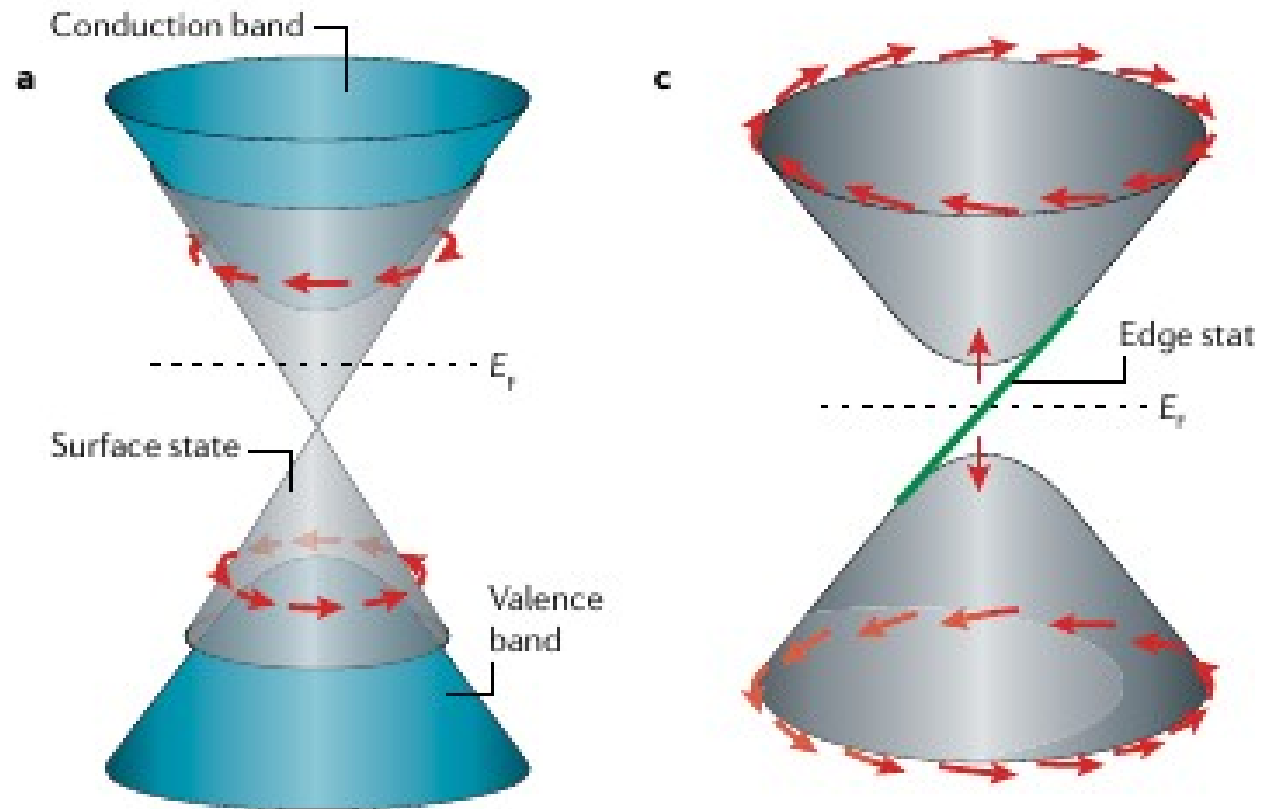
- kvantové počítače
- spintronické součástky
- ...

Topologický izolátor s feromagnetickým uspořádáním:

- Kvantový anomální Hallův jev



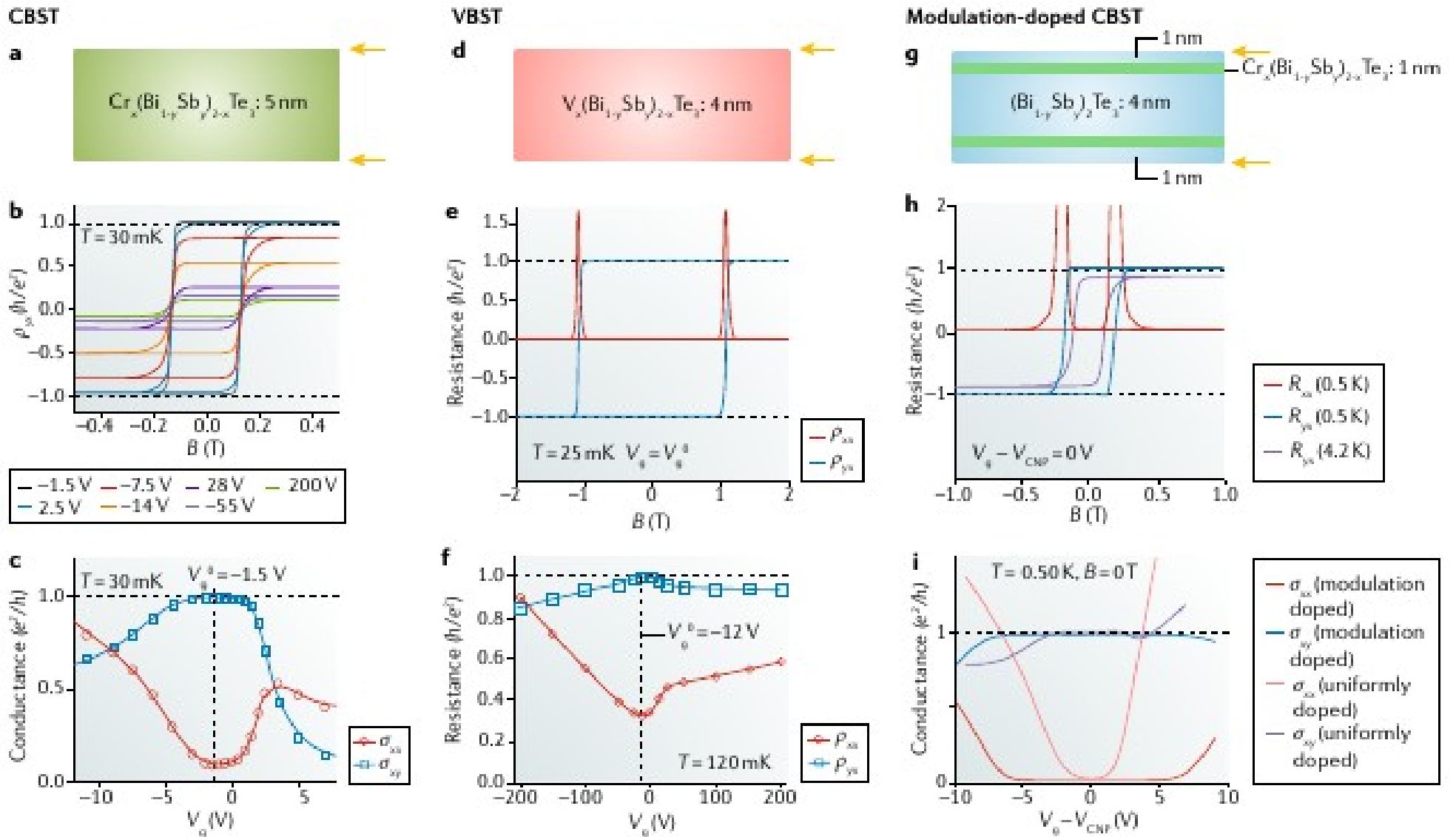
# Topologické izolátory



## Magnetic topological insulators

Yoshinori Tokura<sup>1,2\*</sup>, Kenji Yasuda<sup>1b,2</sup> and Atsushi Tsukazaki<sup>1b,5</sup>

# Topologické izolátory

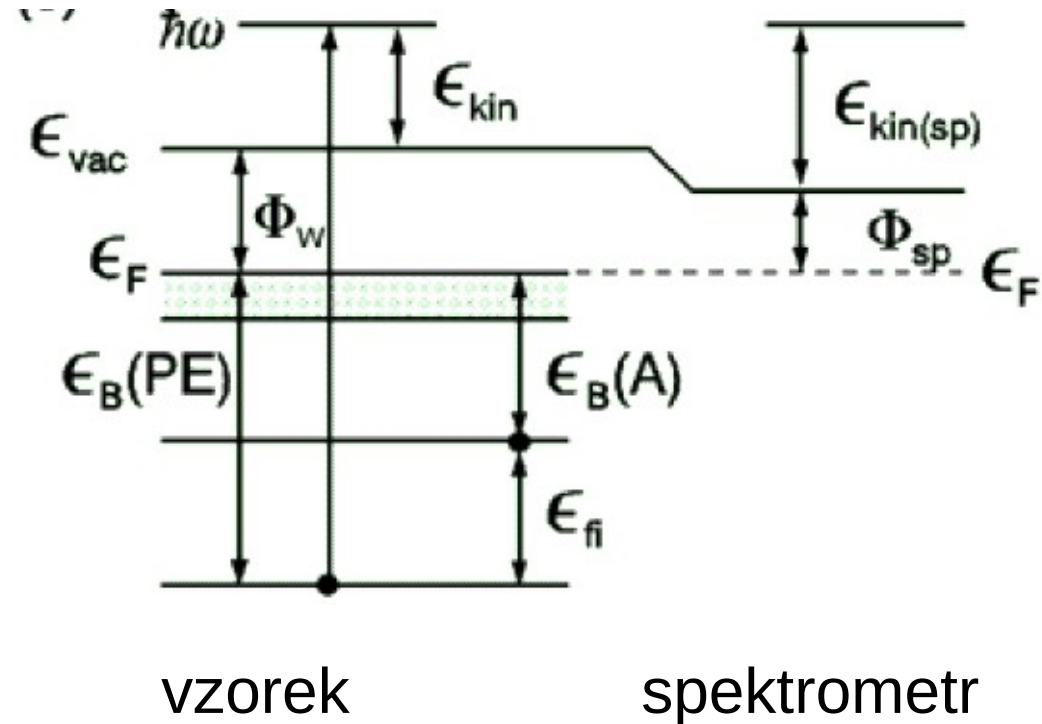
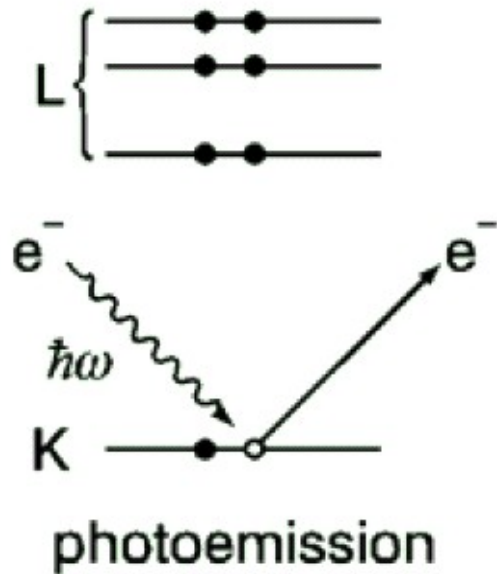


## Magnetic topological insulators

# Fotoemise a Augerův jev

Fotoelektrony – přímo vyražené fotonem

Augerovy elektrony – sekundární emise – alternativní proces ke vzniku charakteristického rtg záření.



# Fotoelektronová spektroskopie

Podmínky experimentu:

Energie fotonů: 10 až 2000eV

Laboratorní zdroje:

- He výbojka 21 eV
- Mg lampa 1254 eV
- Al lampa 1486 eV

Synchrotron – laditelný zdroj

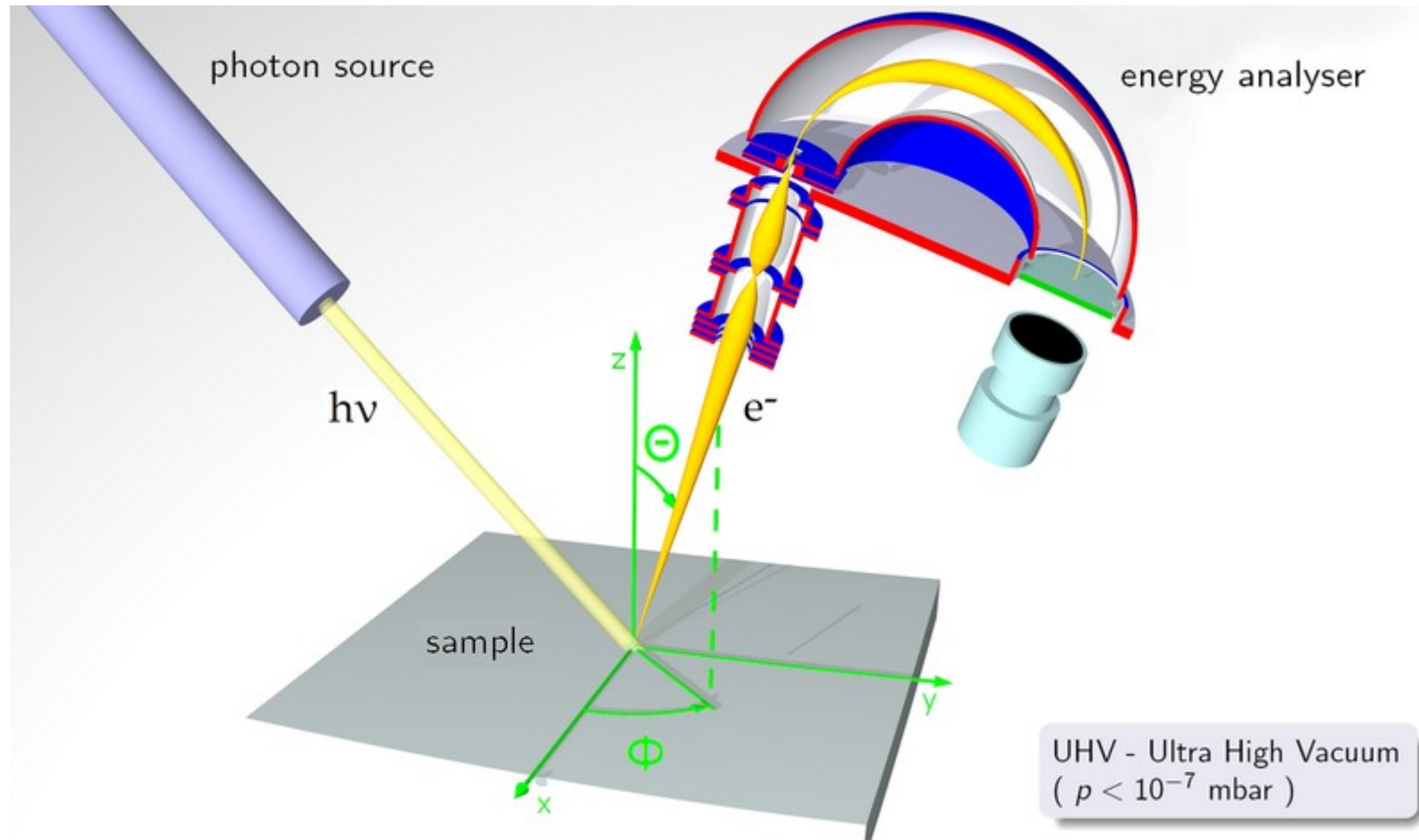
Vysoké vakuum (tlak max  $10^{-6}$  Pa)

Vysoká kvalita a čistota povrchu vzorků

Optika – jen na odraz – zrcadla, difrakční mřížky, žádná okénka!

Hloubka vniku  $10^0$  –  $10^1$  nm

# ARPES - úhlově rozlišená



# ARPES

## Zákony zachování

- Kvaziimpulz – zachovává se tečná složka

$$\hbar\vec{k}_{\text{foton},\parallel} + \hbar\vec{k}_{i,\parallel} = \hbar\vec{k}_{f,\parallel}$$

$$\hbar\vec{k}_{i,\parallel} \approx \hbar\vec{k}_{f,\parallel} = \sqrt{2mE} \sin \theta$$

$$\hbar\vec{k}_x = \sqrt{2mE} \sin \theta \cos \phi$$

$$\hbar\vec{k}_y = \sqrt{2mE} \sin \theta \sin \phi$$

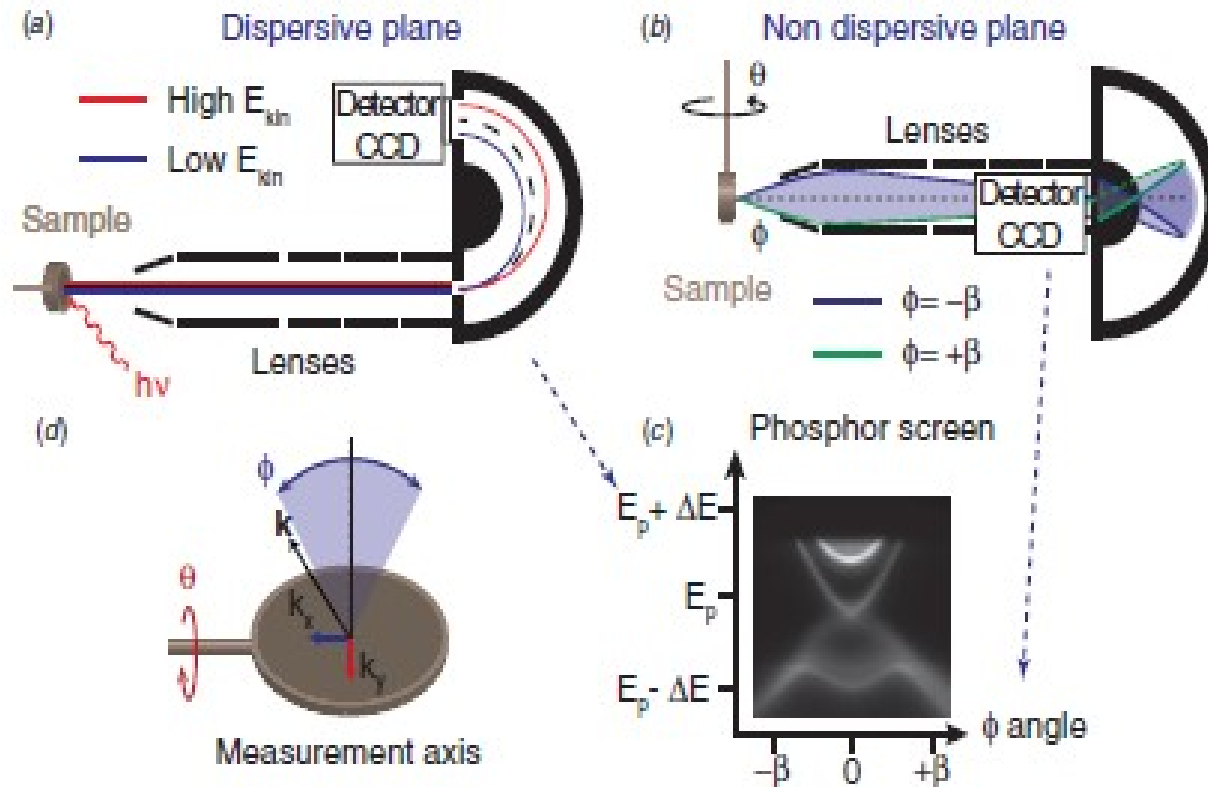
$$\hbar\vec{k}_z = \sqrt{2mE} \cos \theta$$

- energie

$$E_{\text{bound}} = \hbar\omega_i - E_{\text{kin,elektron}} - \varphi$$

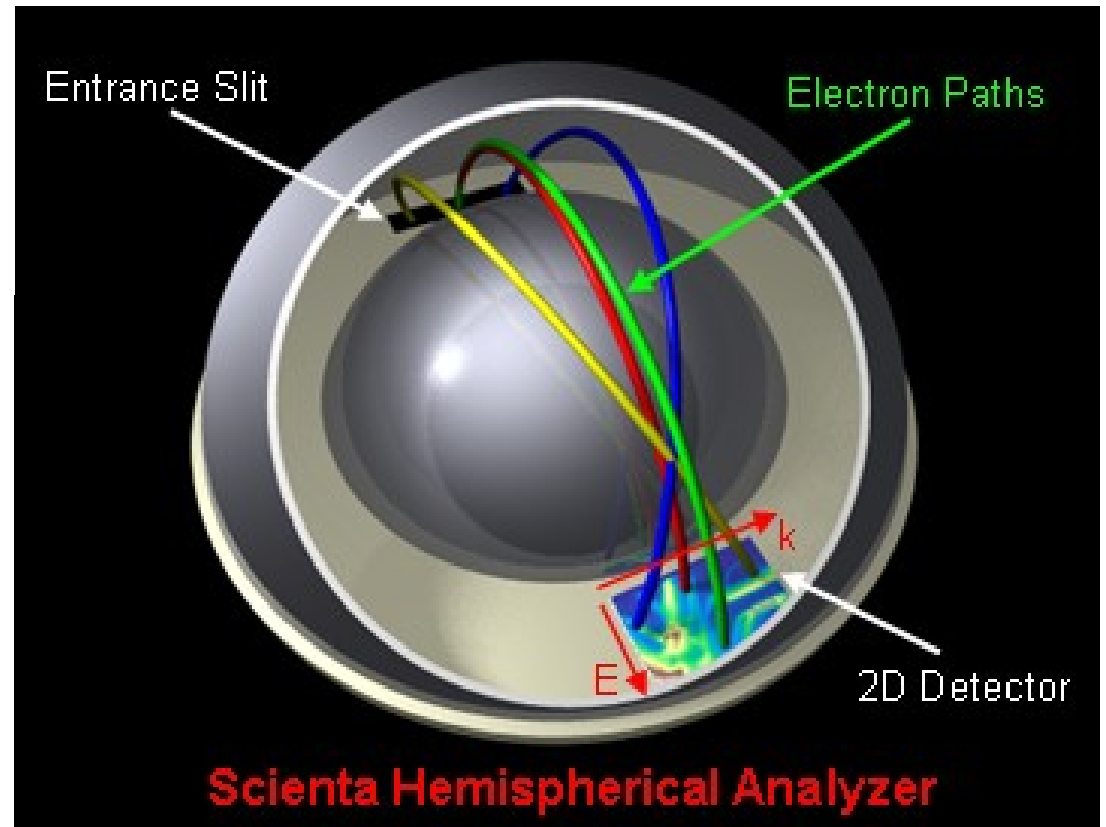
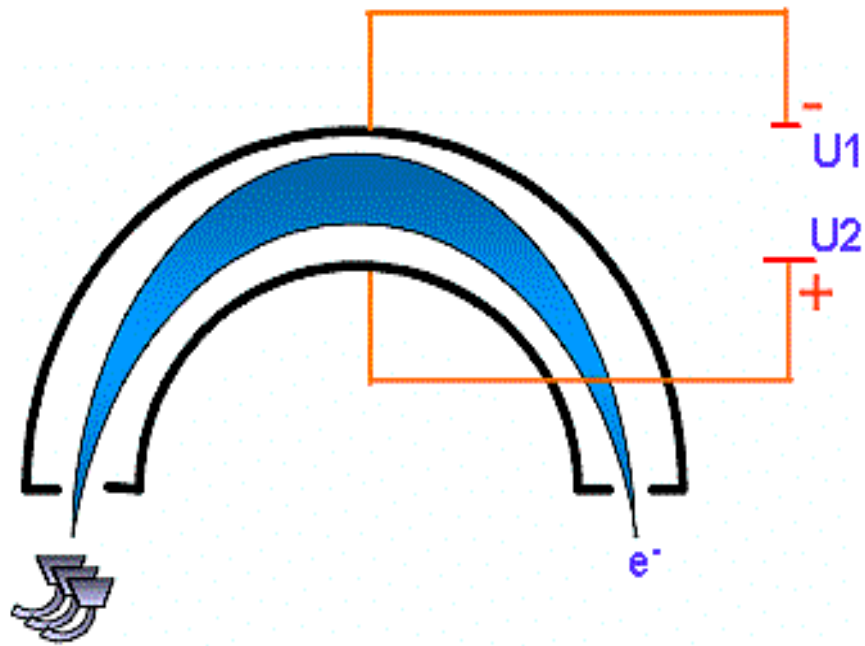
$$\mathbf{k}_{\parallel} = (\sin(\phi)\hat{\mathbf{x}} + \cos(\phi)\sin(\theta)\hat{\mathbf{y}}) \cdot \sqrt{\frac{2m_e E_{\text{kin}}}{\hbar^2}},$$

$$k_z = \sqrt{2m_e / \hbar^2 (V_0 + E_{\text{kin}} \cos(\theta))}.$$



# ARPES

Hemisférický analyzátor + CCD





# Sample preparation

G. Springholz group, JKU Linz

Mn doped  $\text{Bi}_2\text{X}_3$   
thickness 300 to 500nm

Substrate  $\text{BaF}_2$  (111)

Deposition technique:  
Molecular beam epitaxy

Compound sources:  
 $\text{Bi}_2\text{Te}_3$  /  $\text{Bi}_2\text{Se}_3$ , additional Te/Se  
cell to achieve correct  
stoichiometry

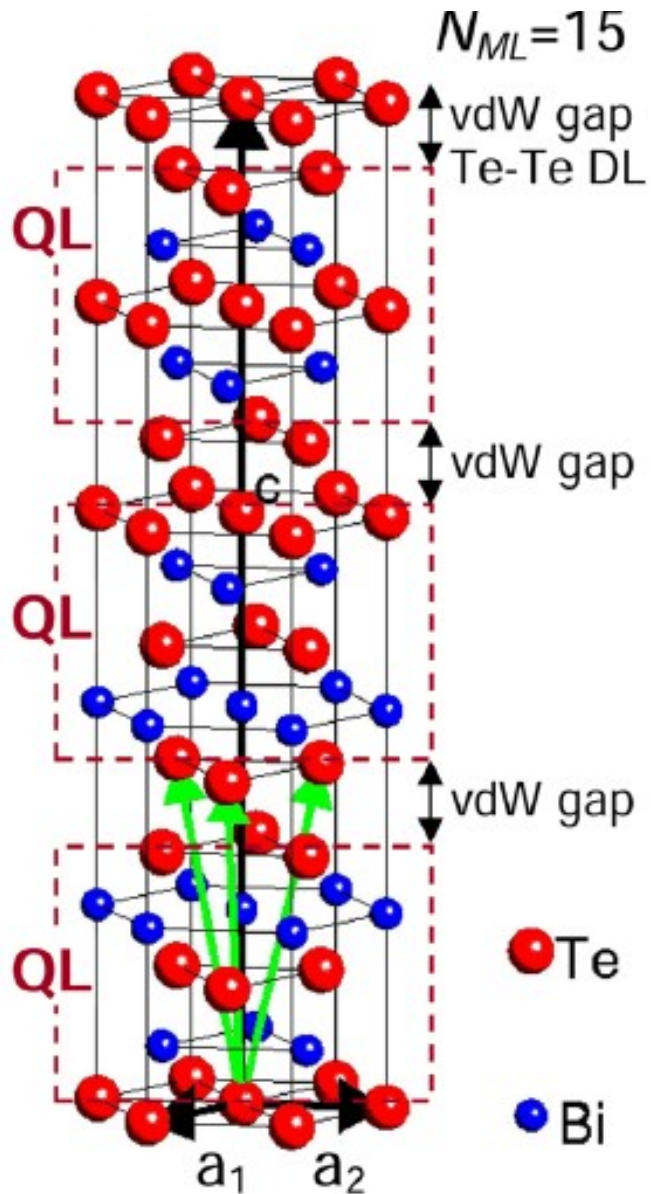
Sample series:

$\text{Bi}_2\text{Te}_3$  up to 11% of Mn doping

$\text{Bi}_2\text{Se}_3$  up to 10% of Mn doping

# Topologické izolátory dopované Mn

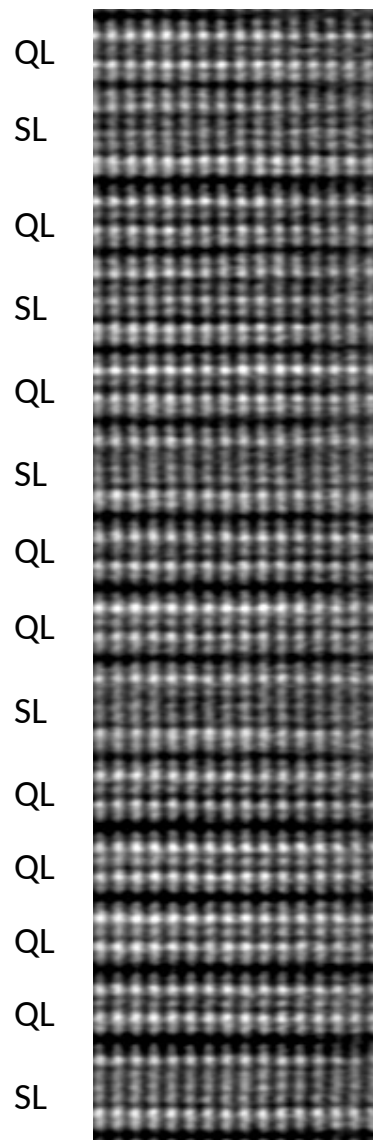
Strukturní analýza vrstev topologických izolátorů



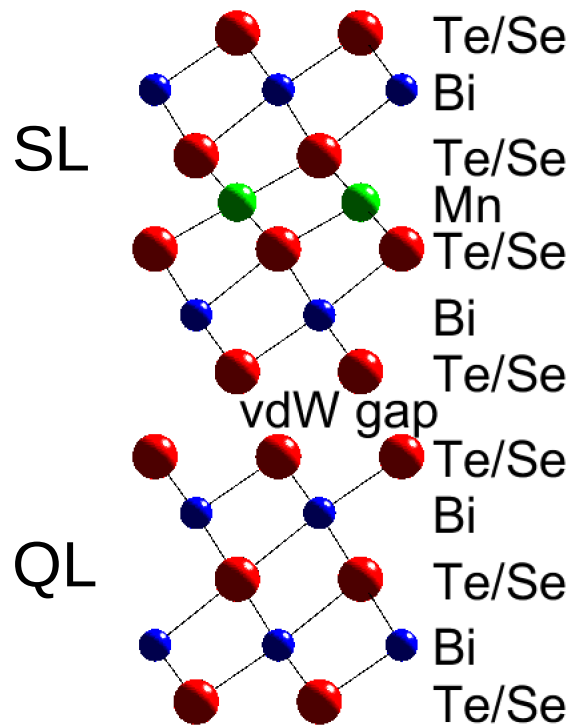
# Electron microscopy

JKU Linz, Graz

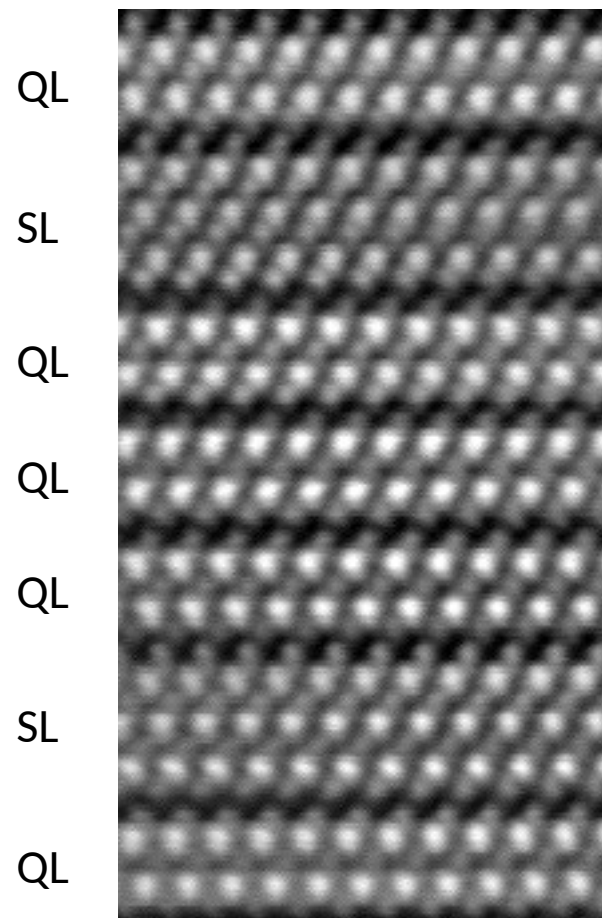
10% Mn Bi<sub>2</sub>Te<sub>3</sub>



HAADF STEM



6% MnBi<sub>2</sub>Se<sub>3</sub>

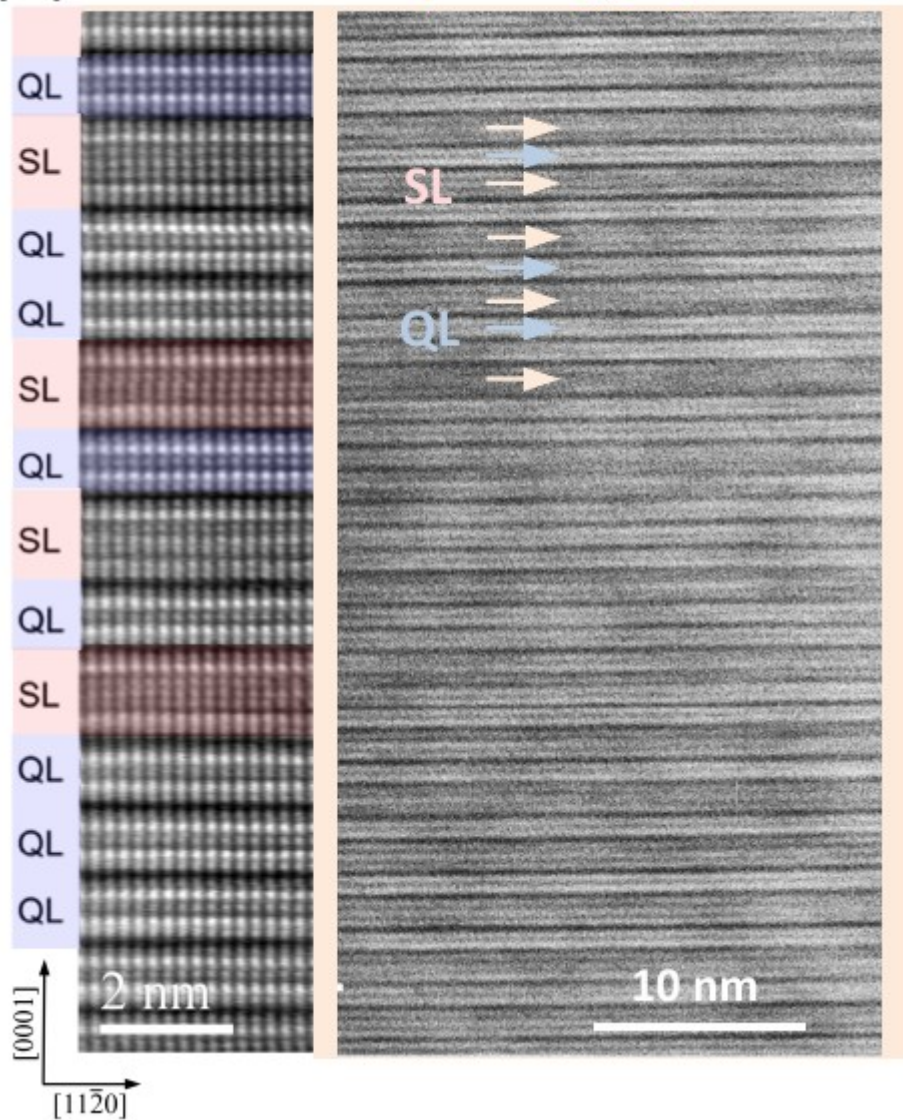


# Topologické izolátory dopované Mn

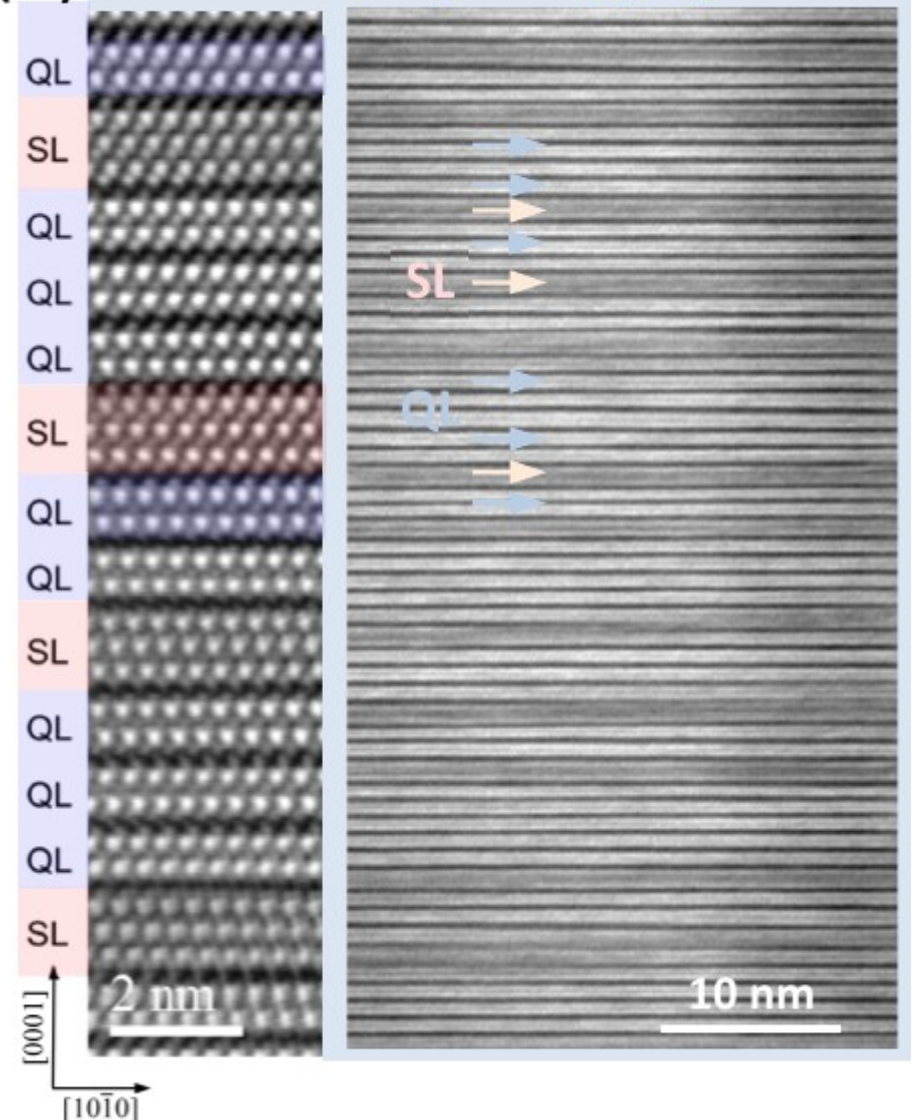
Strukturní analýza vrstev topologických izolátorů

HAADF-STEM (příprava lamel ZONA JKU Linz, TEM Graz)

(a) Mn-doped  $\text{Bi}_2\text{Te}_3$



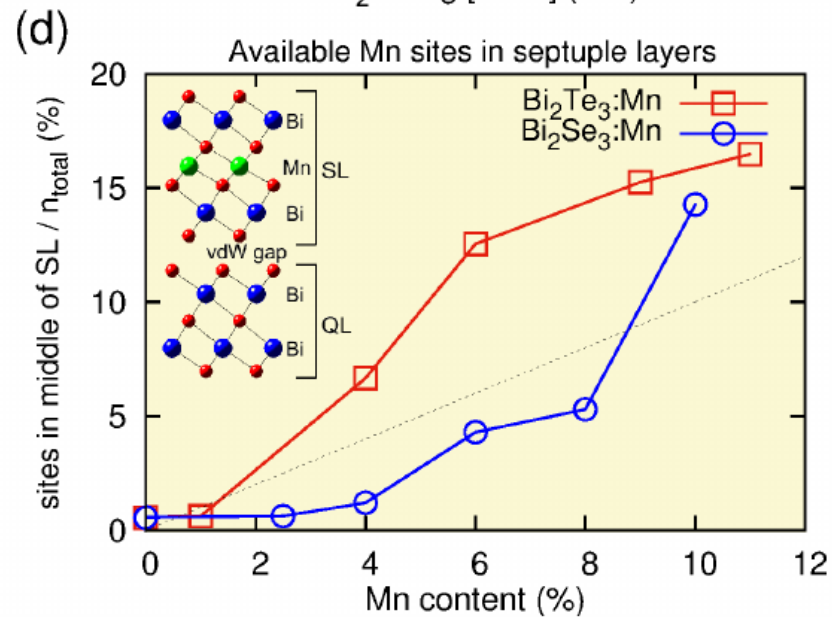
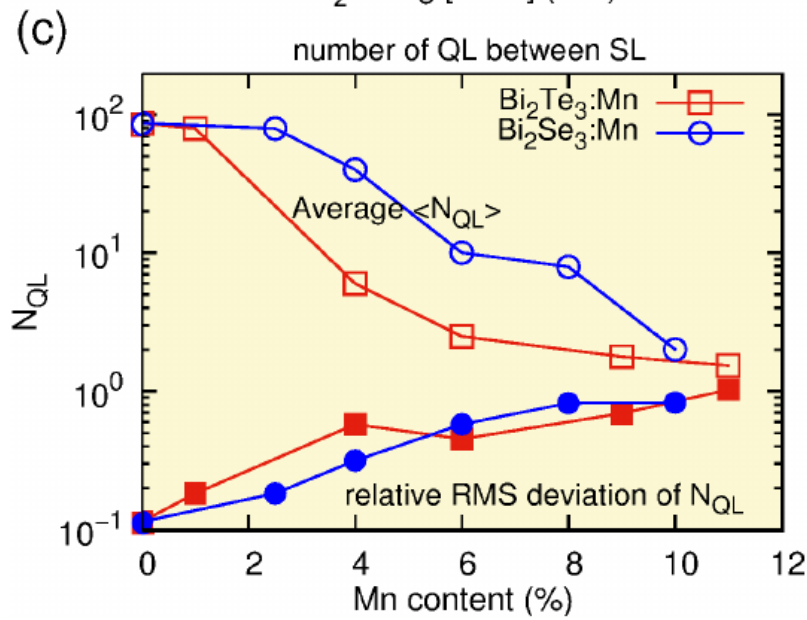
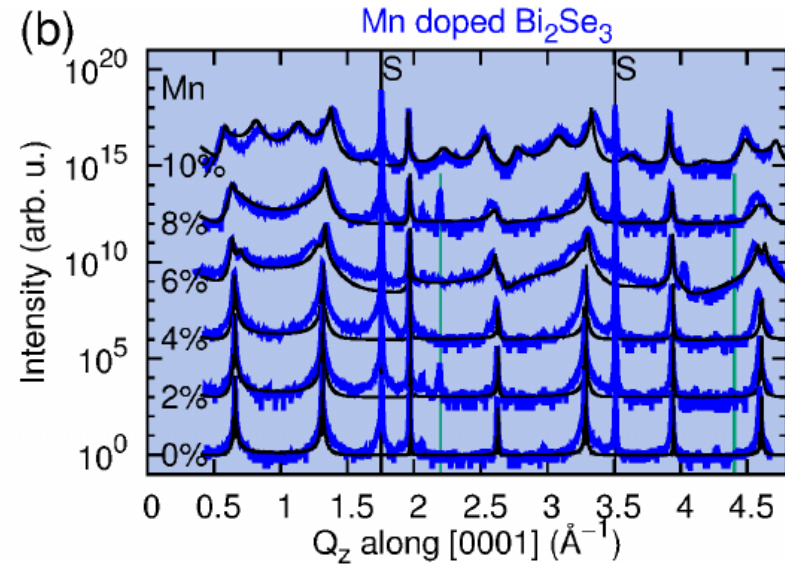
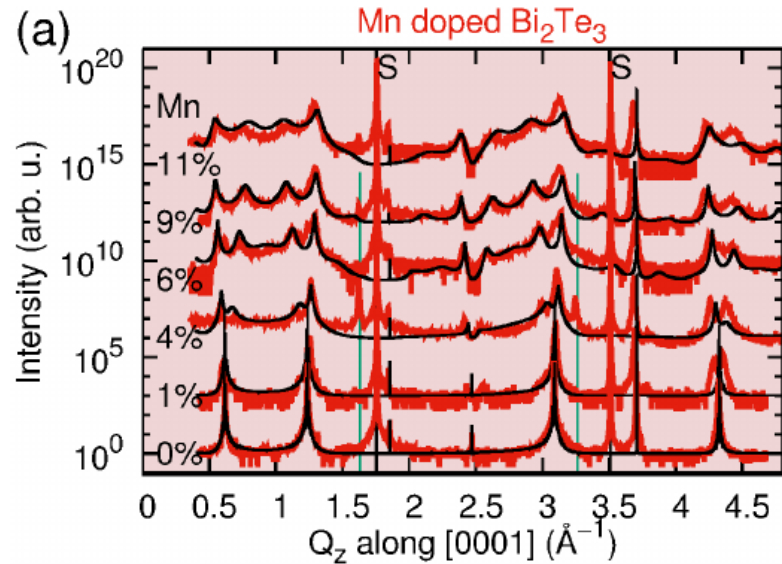
(b) Mn-doped  $\text{Bi}_2\text{Se}_3$



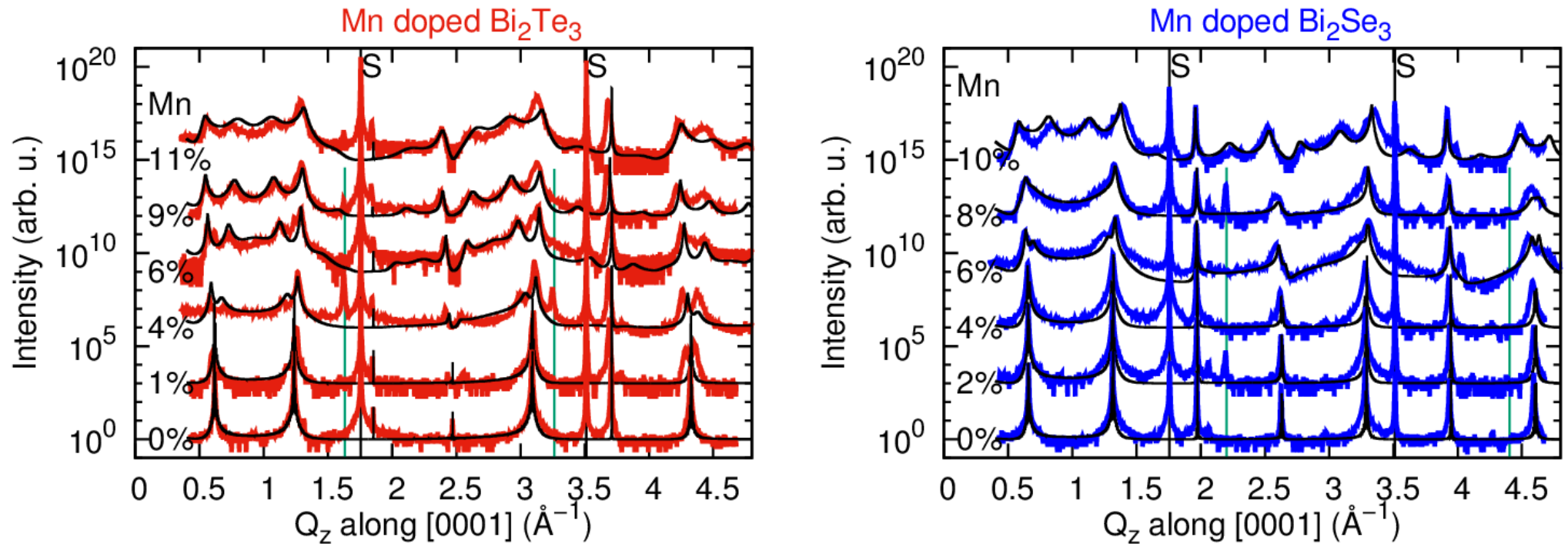
# Topologické izolátory dopované Mn

Strukturní analýza vrstev topologických izolátorů

fitováno modelem parakrystalu



# XRD structure analysis



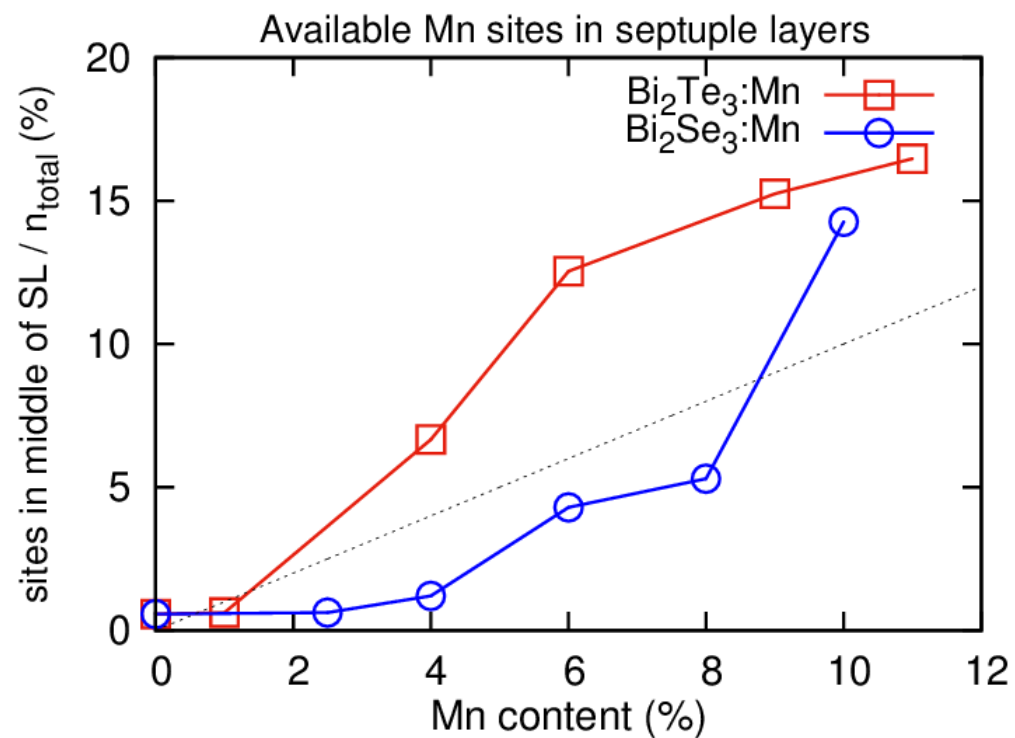
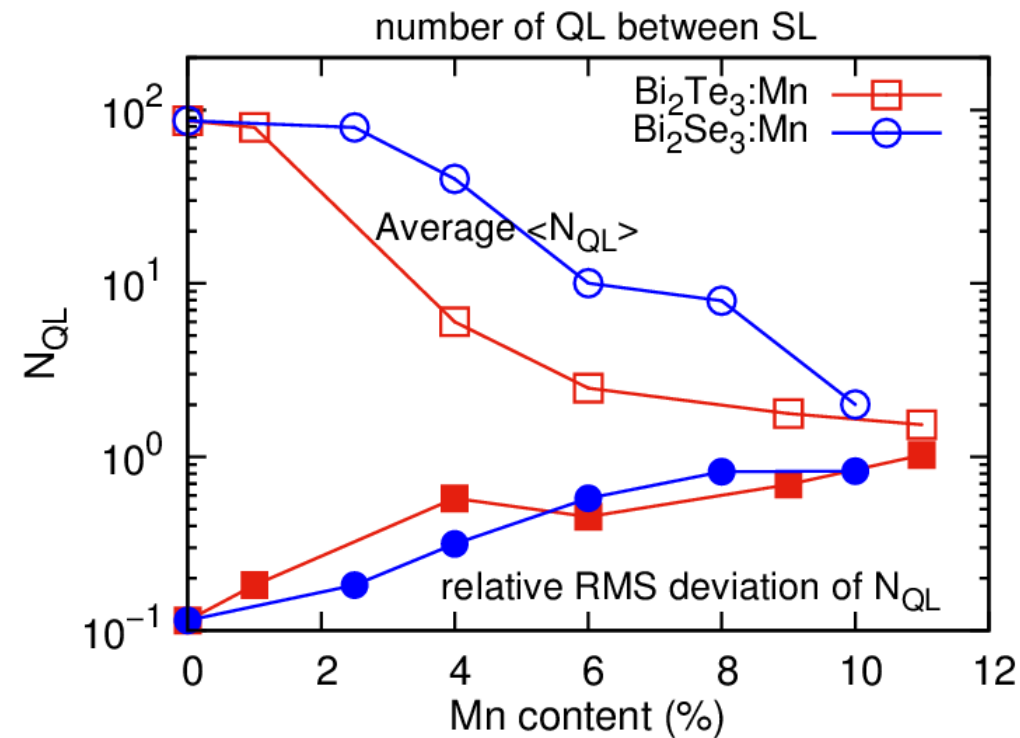
Symmetric scan with scattering vector perpendicular to the surface

Higher Mn content leads to disturbed structure

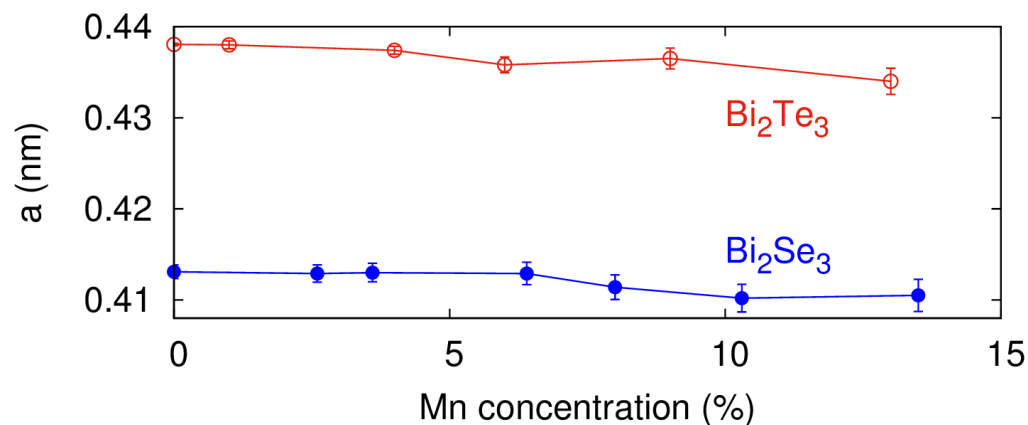
Fitted with a paracrystal model:

Random sequence of  $\text{Bi}_2\text{X}_3$  (quintuple layers – QL) and  $\text{Bi}_2\text{MnX}_4$  (septuple layer – SL)

# XRD structure analysis



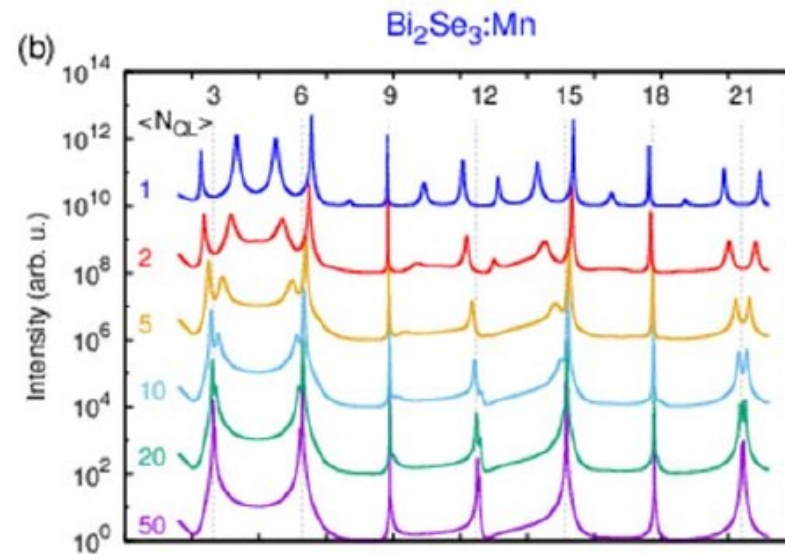
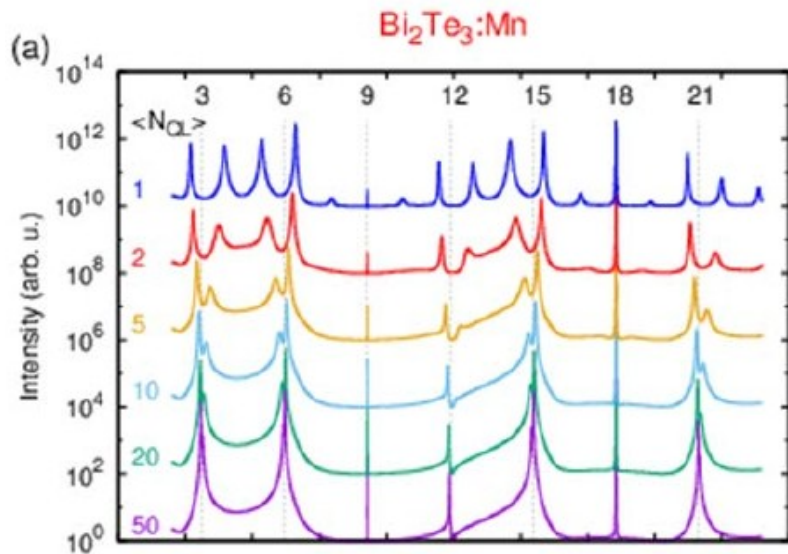
## In-plane lattice parameter dependence



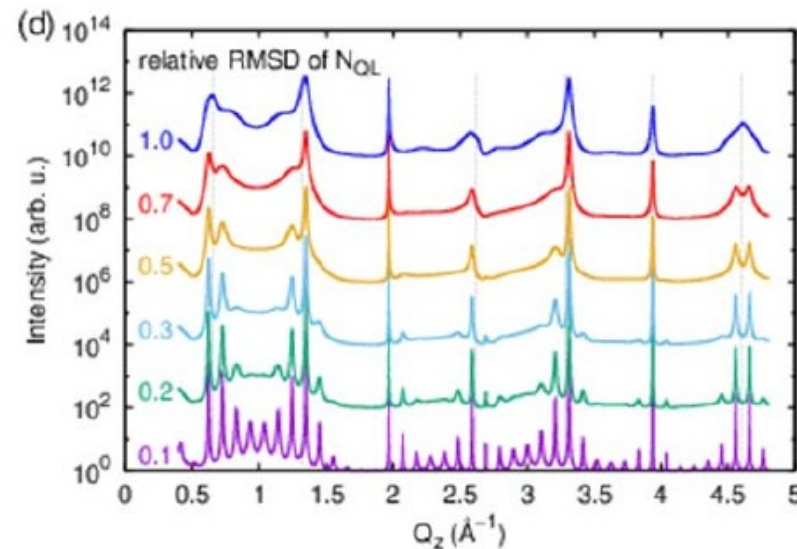
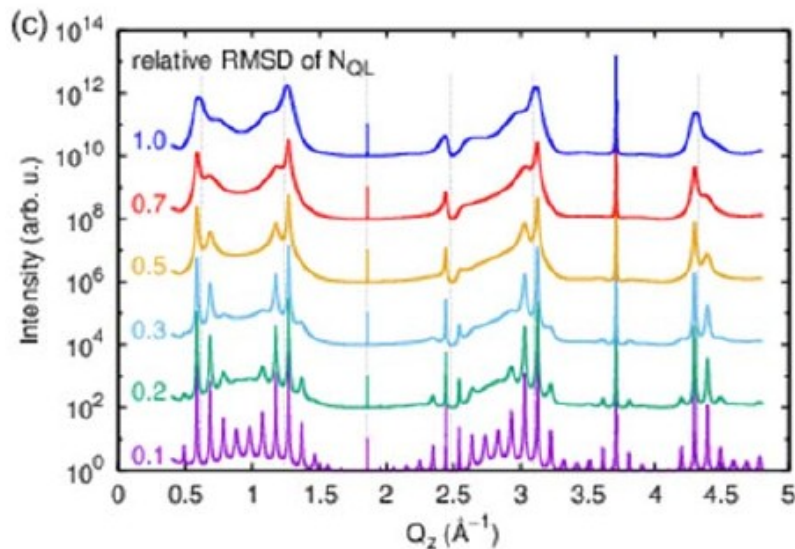
# Topologické izolátory dopované Mn

Strukturní analýza vrstev topologických izolátorů

fitováno modelem parakrystalu



relative  
RMSD = 0.5

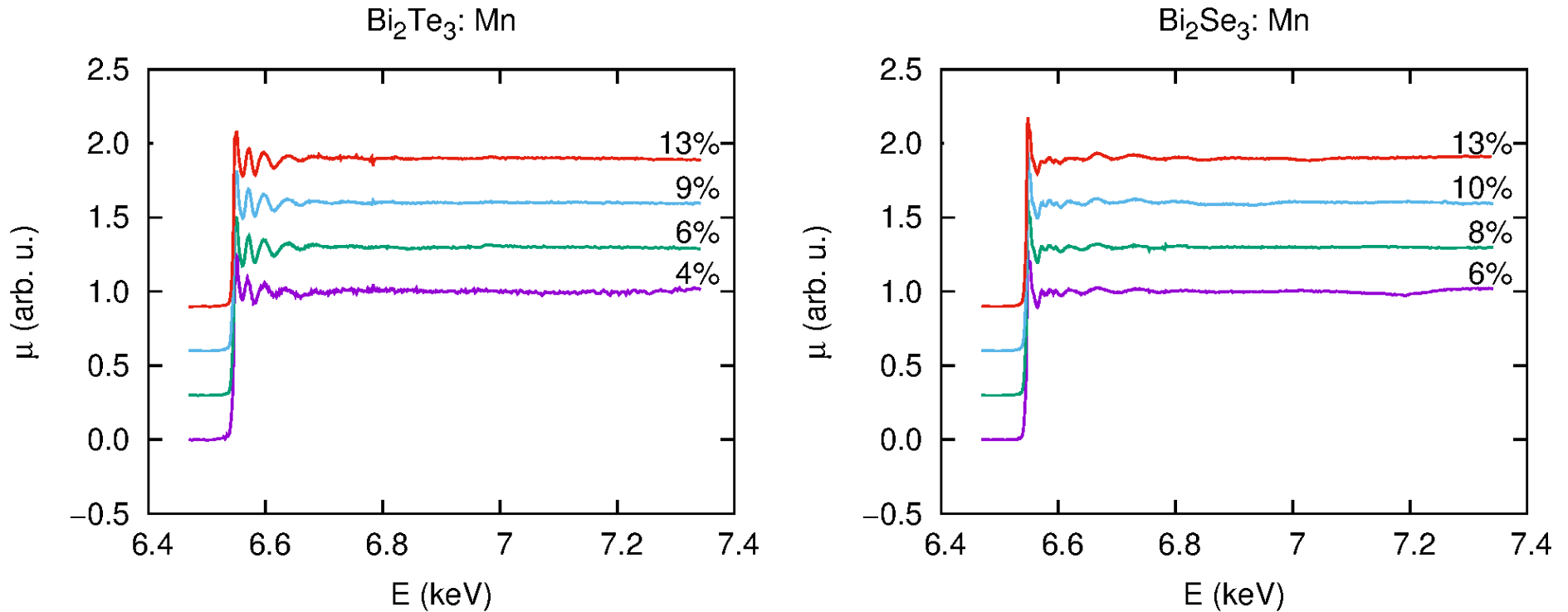


$\langle N_{\text{QL}} \rangle = 5$



# X-ray absorption spectroscopy

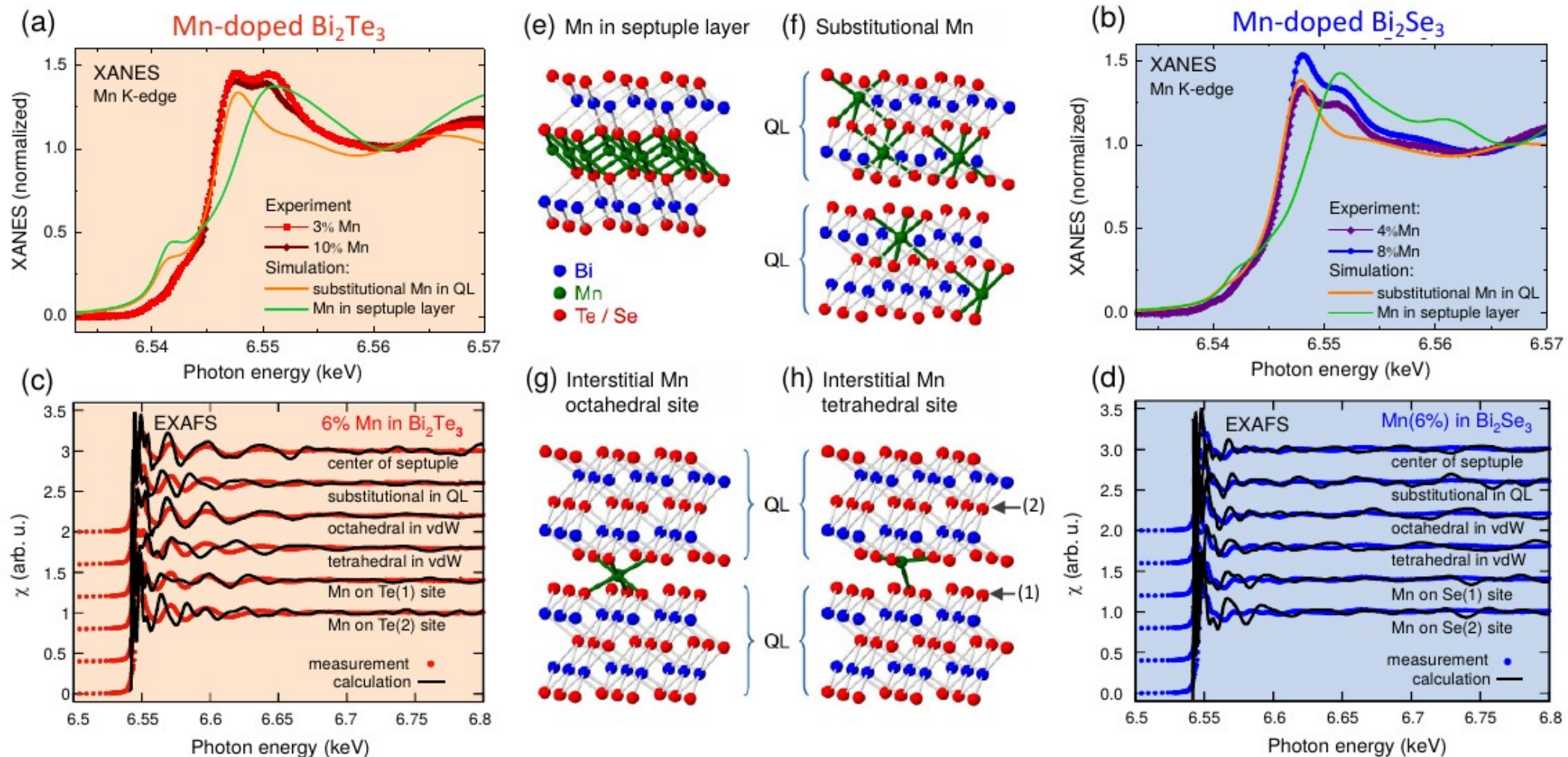
Experiment at BM23, ESRF Grenoble



Very weak Mn concentration dependence

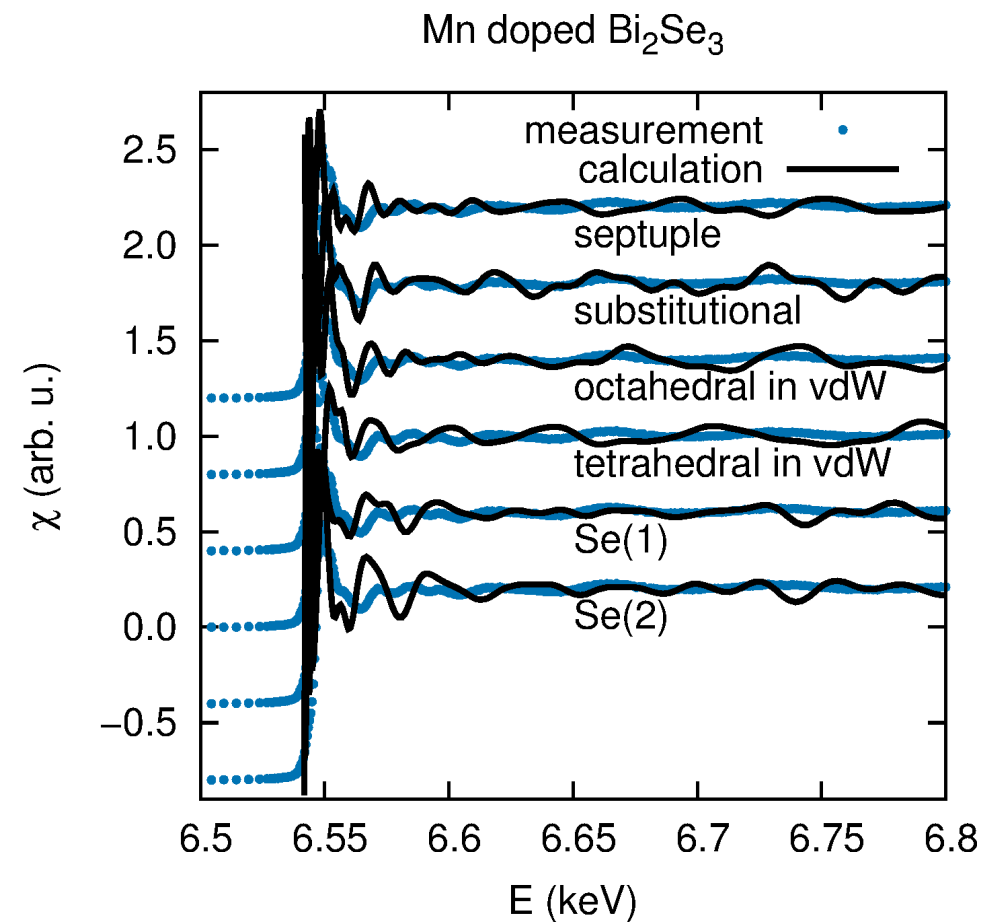
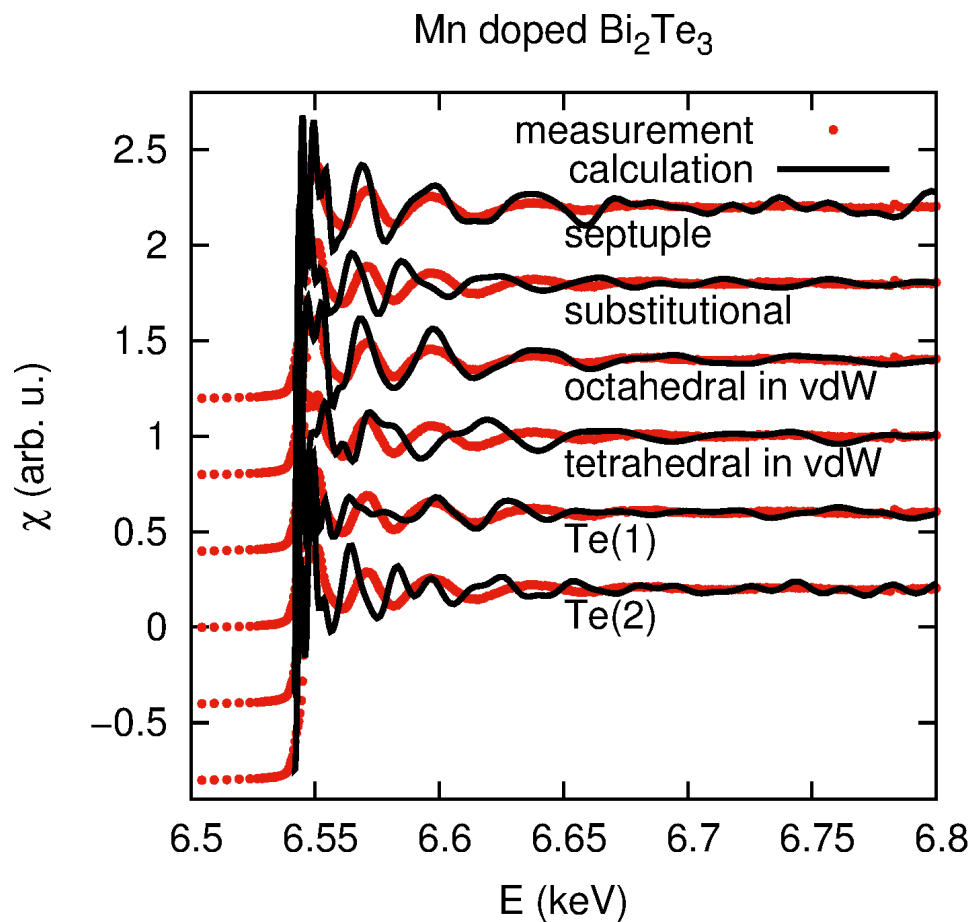
# Topologické izolátory dopované Mn

## Strukturní analýza vrstev topologických izolátorů



# X-ray absorption spectroscopy

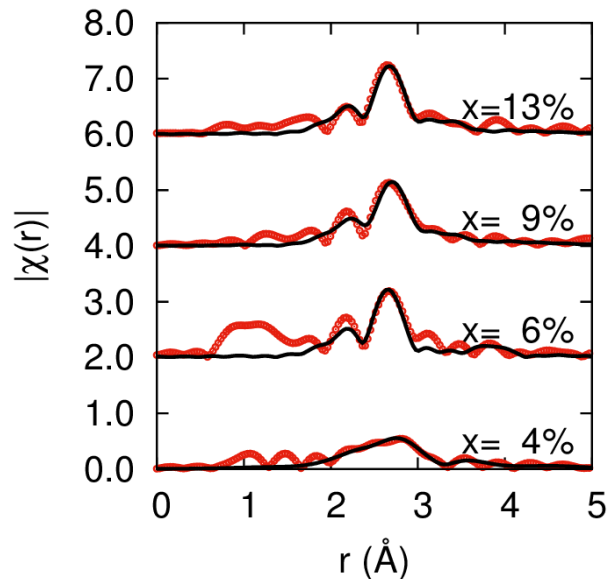
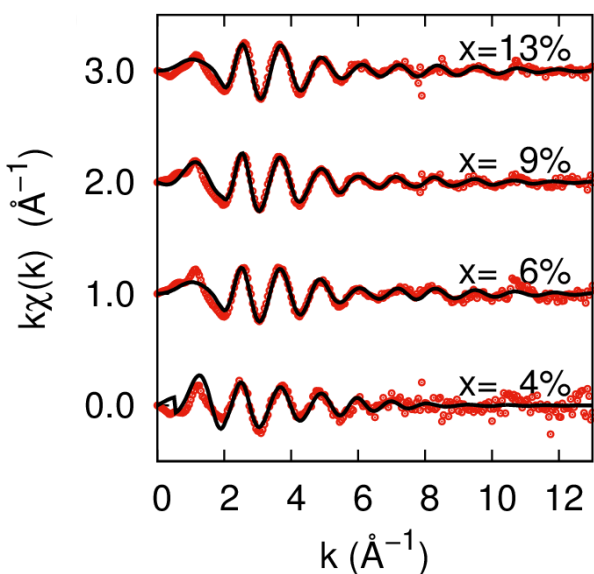
Simulations of various Mn positions



# X-ray absorption spectroscopy

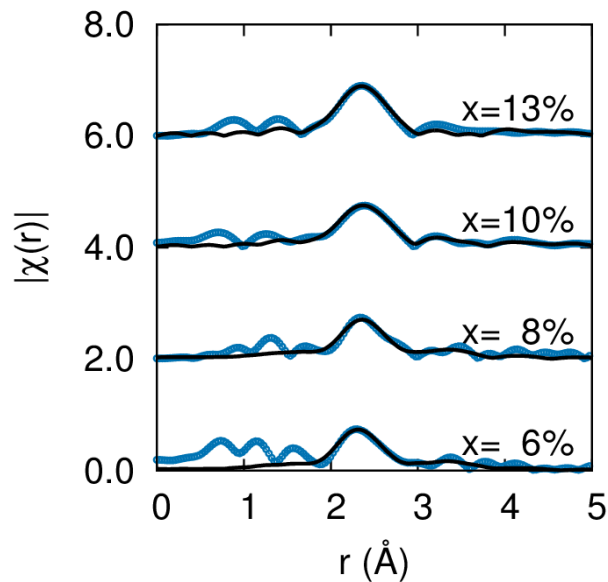
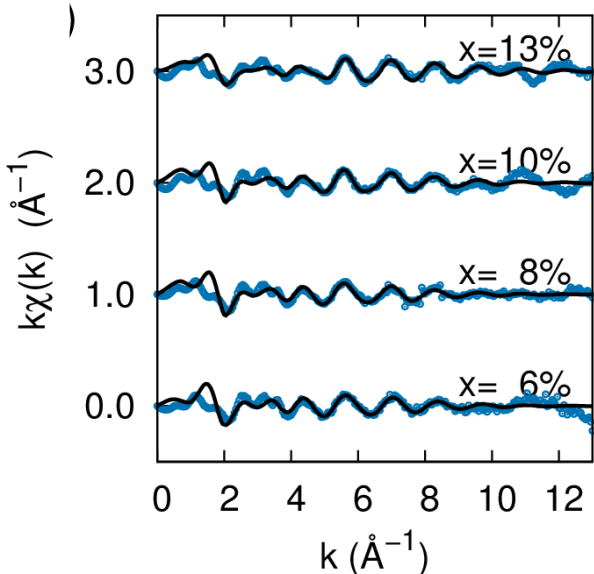
## Fitted distances of Mn nearest neighbors

Mn doped  $\text{Bi}_2\text{Te}_3$



<b><math>\text{Bi}_2\text{Te}_3</math>: Mn</b>	
Mn content (%)	NN distance ( $\text{\AA}$ ) 6 Te atoms
4	$2.90 \pm 0.09$
6	$2.92 \pm 0.04$
9	$2.92 \pm 0.04$
13	$2.91 \pm 0.06$

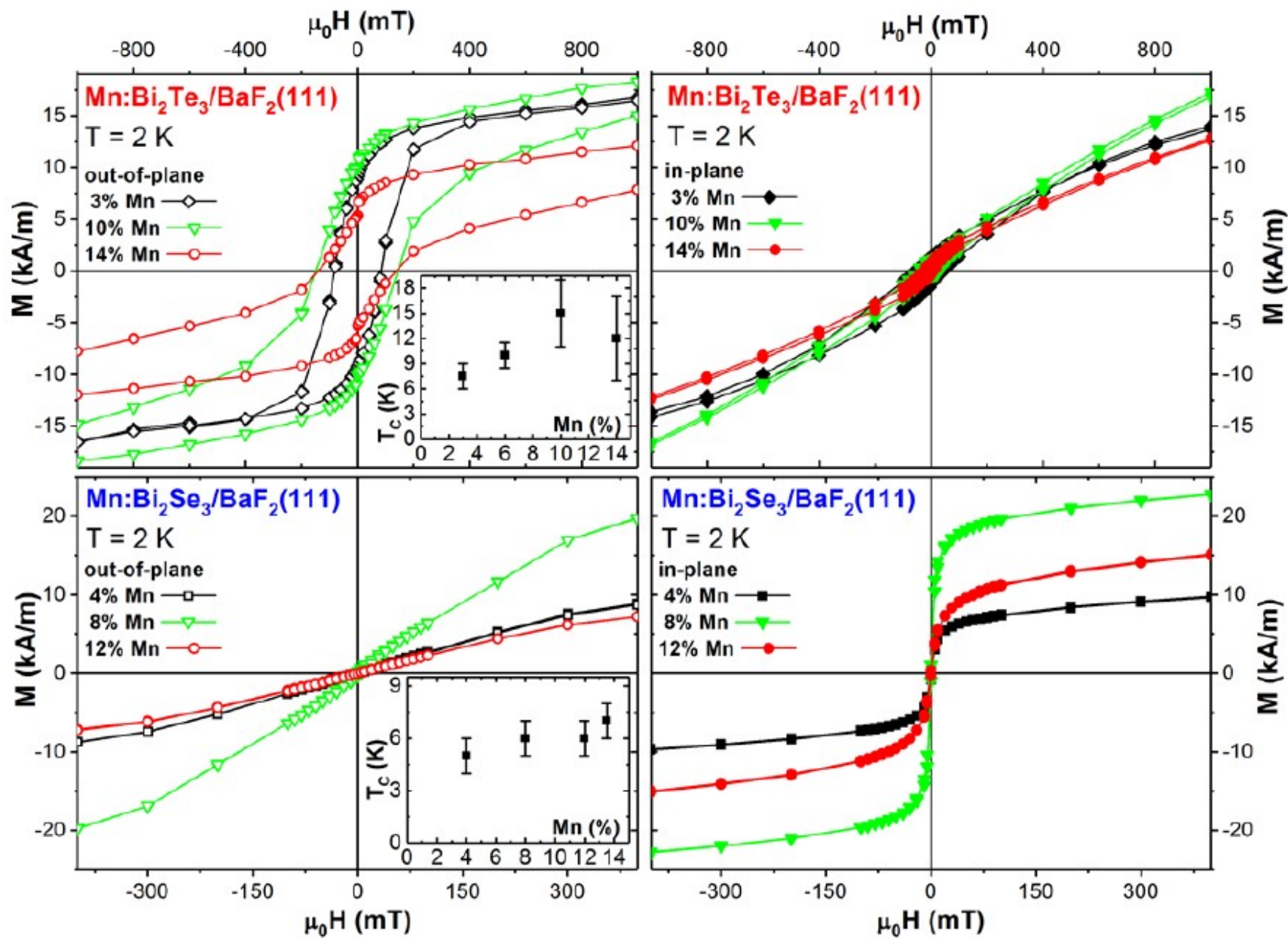
Mn doped  $\text{Bi}_2\text{Se}_3$



<b><math>\text{Bi}_2\text{Se}_3</math>: Mn</b>	
Mn content (%)	NN distance ( $\text{\AA}$ ) 6 Se atoms
4	$2.75 \pm 0.08$
6	$2.67 \pm 0.04$
8	$2.71 \pm 0.04$
10	$2.72 \pm 0.03$
13	$2.71 \pm 0.04$

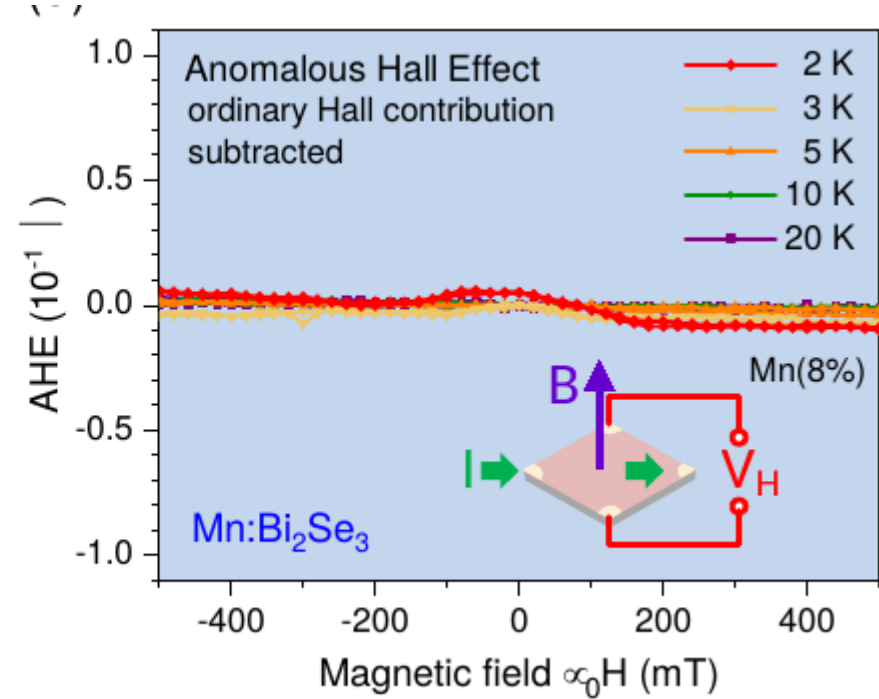
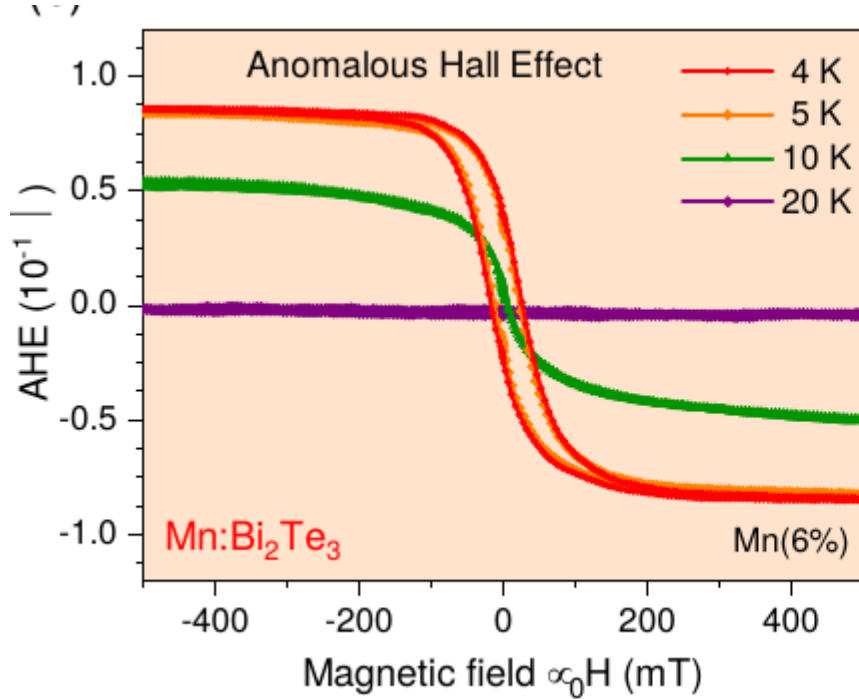
# Topologické izolátory dopované Mn

Magnetické vlastnosti vrstev topologických izolátorů  
SQUID (JKU Linz)



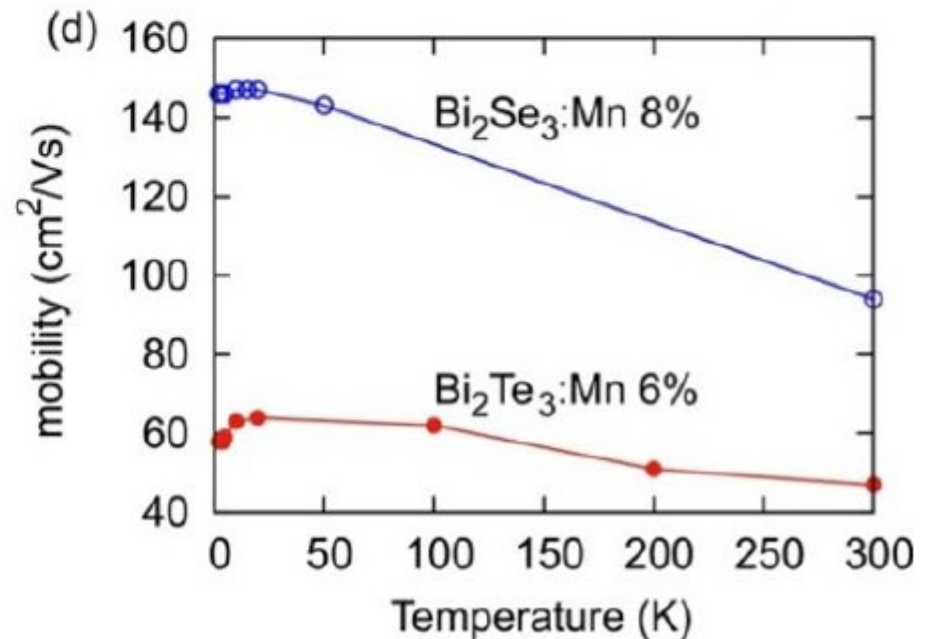
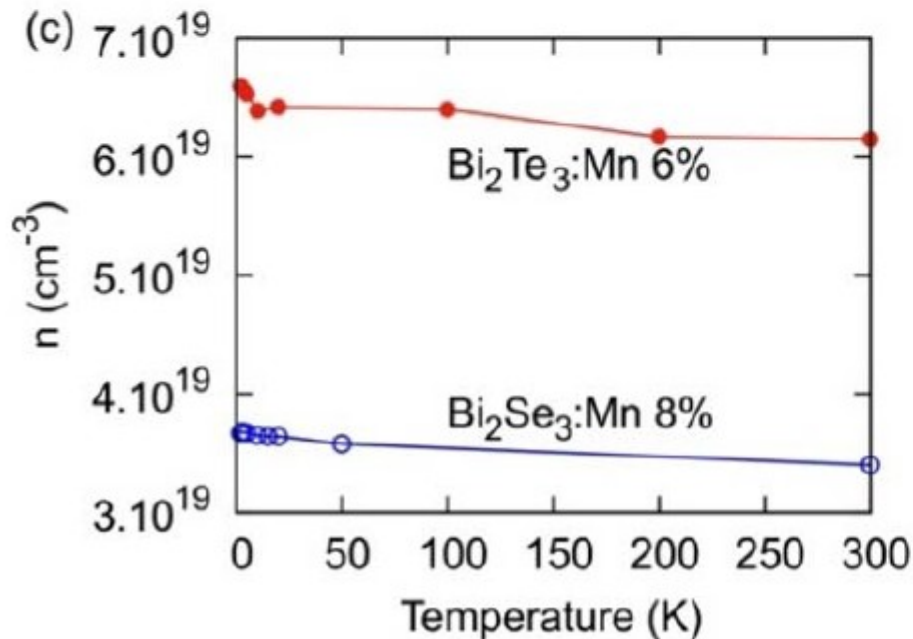
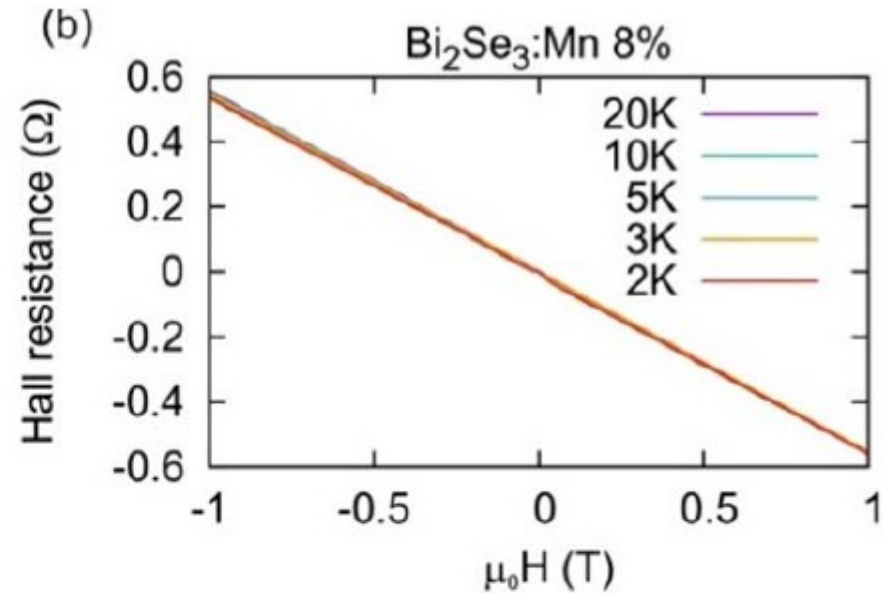
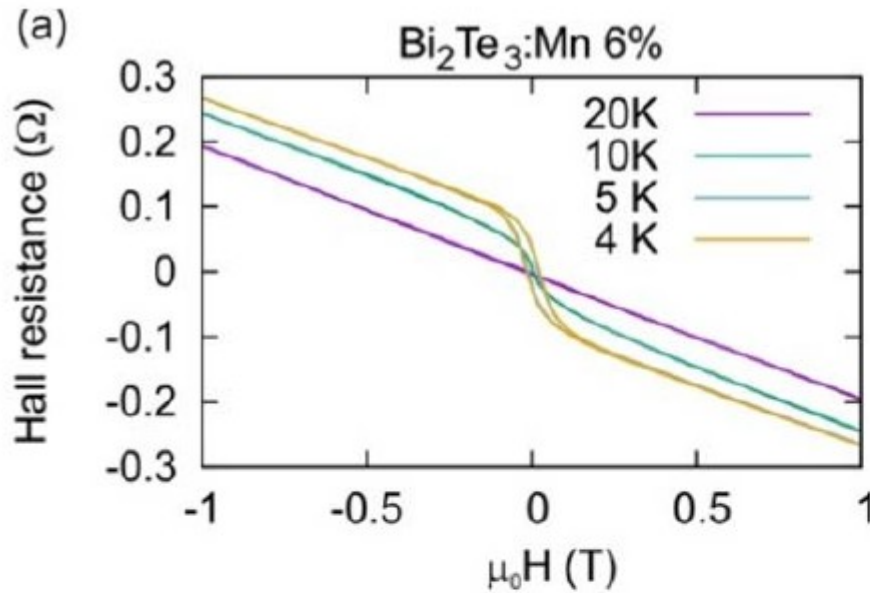
# Topologické izolátory dopované Mn

Magnetické vlastnosti vrstev topologických izolátorů - CEITEC



# Topologické izolátory dopované Mn

Magnetické vlastnosti vrstev topologických izolátorů - CEITEC



# Electronic structure

ARPES BESSYII, HZB Berlin

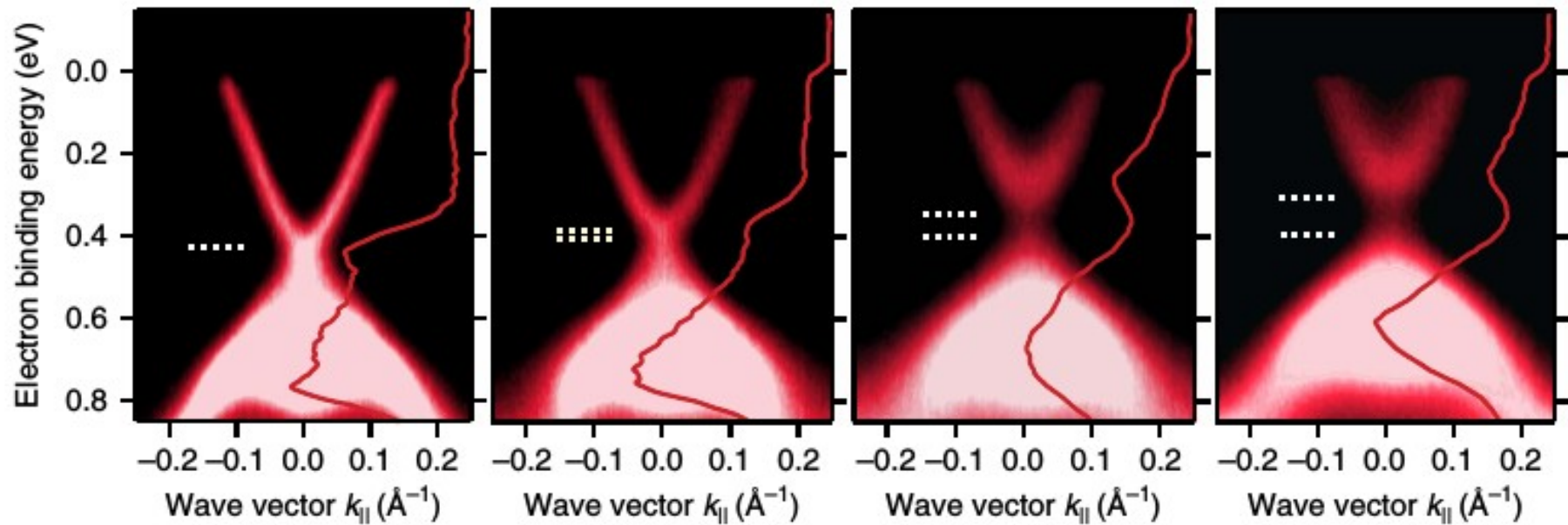
$\text{Bi}_2\text{Se}_3$ , 12K

Mn 0%

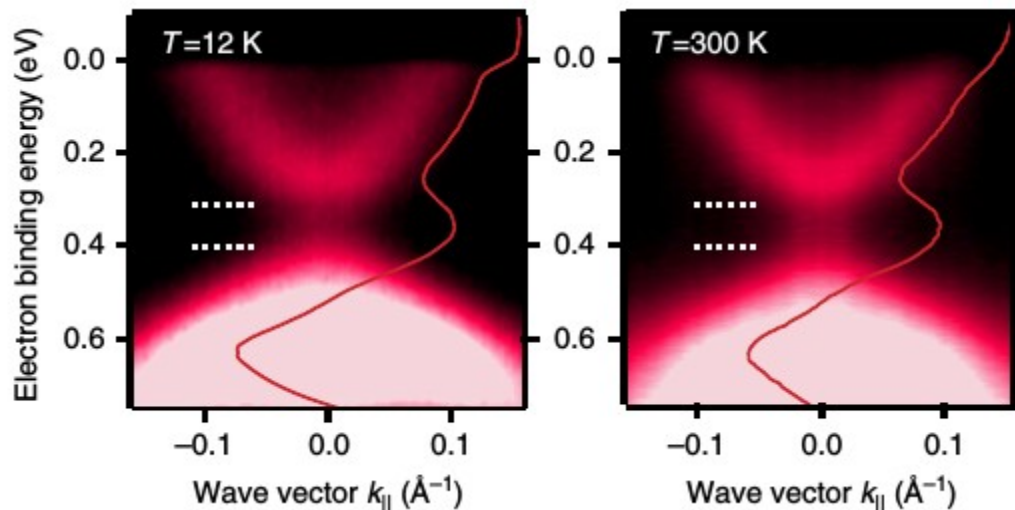
2%

4%

8%



Mn 8%

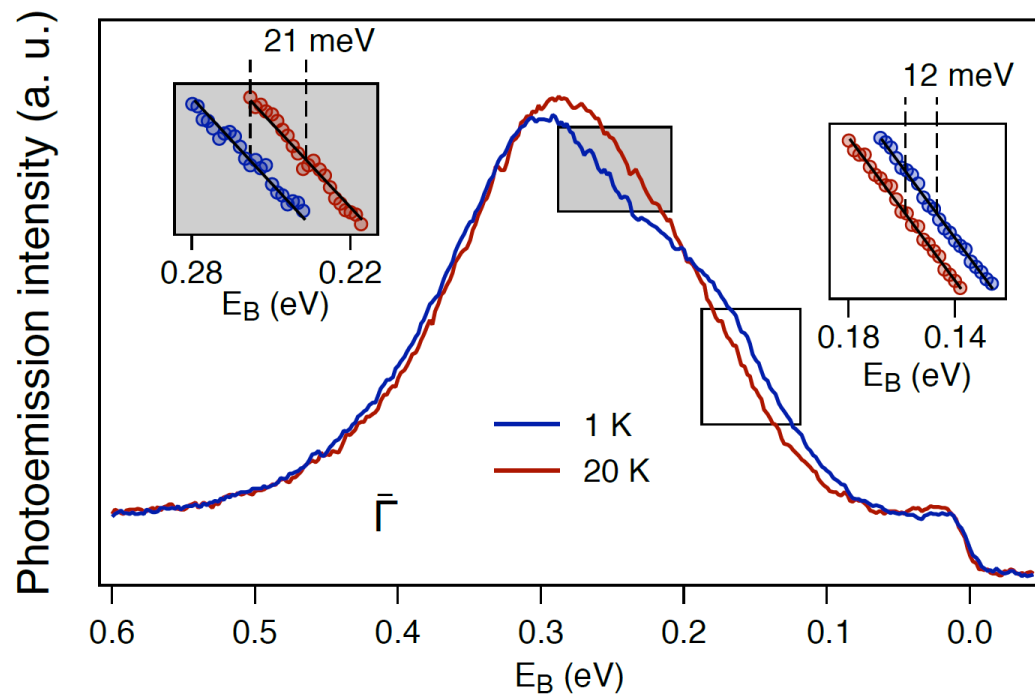
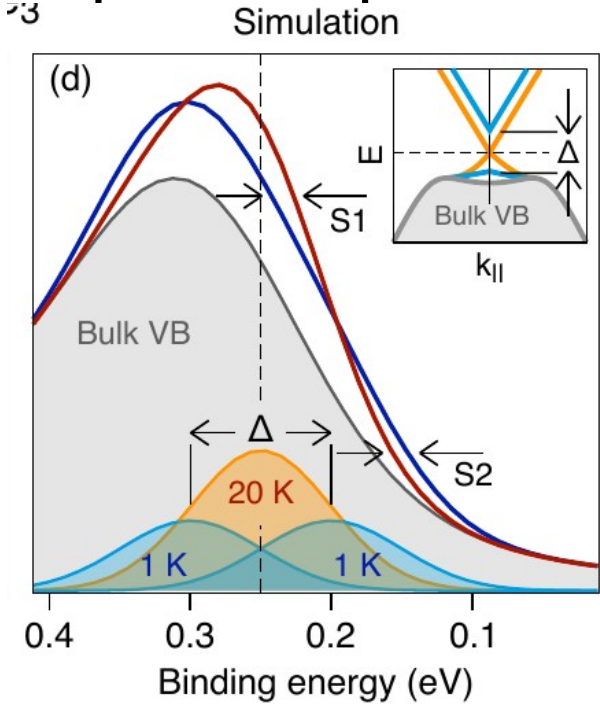
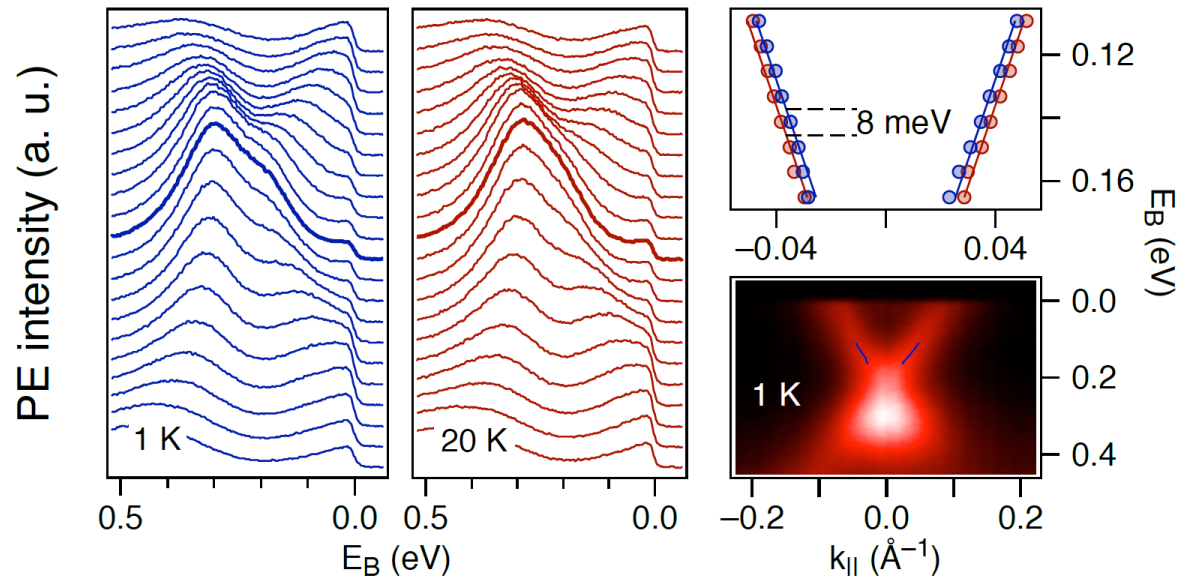


J. Sanchez-Barriga et al., Nature Comm. 7:10559 (2015).



# Electronic structure

ARPES BESSYII, HZB Berlin,  $\text{Bi}_2\text{Te}_3$  6% Mn doped samples



Magnetic gap 90 meV

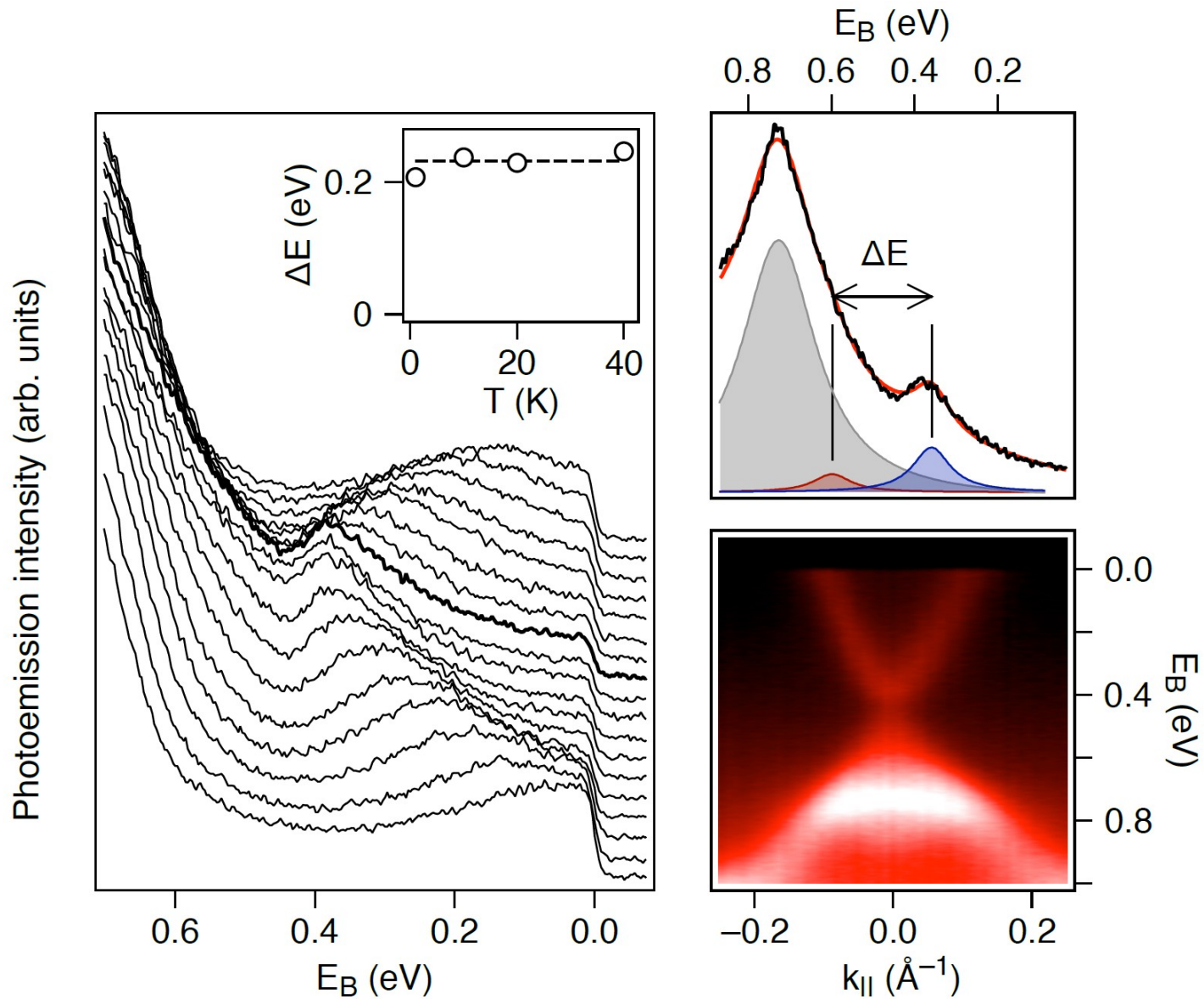
DFT theoretical prediction  
 $\approx 16$  meV for 10% Mn

Henk et al., Phys. Rev. Lett **109**, 076801 (2011).

$\approx 40$ -80 meV for heterostructure  
 Otrokov et al., 2D mater. **4**, 025082 (2017).

# Electronic structure

6% Mn doped  $\text{Bi}_2\text{Se}_3$  at 1K



Temperature independent nonmagnetic gap 200 meV

# Conclusion

- Mn doped topological insulators form natural heterostructure of alternating QL and SL segments
- Mn atoms are mostly positioned in the central position of septuple layer
- Ferromagnetic ordering has been observed with Curie temperature in range of 6K to 15K for Mn concentration above 3%
- Easy magnetization axis is:
  - Out-of-plane for bismuth telluride
  - In-plane for bismuth selenide
- Bismuth telluride shows large magnetic band gap of  $(90 \pm 10)$  meV opened below Curie temperature
- Bismuth selenide does show temperature independent band gap of  $\approx 200$  meV

# Topologické izolátory dopované Mn

Závěr:

určili jsme strukturu vrstev, uspořádání Mn

Feromagnetické pod cca 15K

Směr snadné magnetizace kolmo k povrchu (telurid), v rovině (selenid)

Pozorován gap v pásové struktuře indukovaný feromagnetickým přechodem